EFFECTS OF TiO$_2$ COMPACT LAYER ON PHOTOVOLTAIC
CHARACTERISTICS OF TiO$_2$/Nb$_2$O$_5$ DYE SENSITIZED SOLAR CELLS

BY

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Master of Science (MSc) in Physics of University of Nairobi

2019
DECLARATION

Declaration by the candidate

I declare that this thesis is my original work and has not been submitted elsewhere for examination, award of a degree or publication. Where other people’s work or my own work has been used, this has properly been acknowledged and referenced in accordance with the University of Nairobi’s policy requirements.

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This work is dedicated to my respected parents.
ACKNOWLEDGEMENT

I would like to express my heartiest gratitude and sincere appreciation to my advisors; Prof. Francis W. Nyongesa, Prof. Bernard O. Aduda and Dr. Alex A. Ogachó for their diligent effort and commitment in guiding me through this research work. I could have not made it without their good faith in my efforts, honest criticism and guidance. I am grateful to Mr. Victor Odari for his valuable suggestions and assistance during the research. I am greatly indebted to the University of Nairobi for the provision of scholarship that enabled me complete this research and to International Science Program (ISP) for the financial support they gave me. Finally, I would like to thank my family: my parents and my siblings for supporting me spiritually throughout the pursuit of my M.Sc. I am thankful to my friends who supported me as well.
Titanium dioxide has been widely used in dye sensitized solar cells as a semiconductor, however, the recombination rate of photo generated hole-electron pairs on TiO$_2$ is very high which reduces its electron transport efficiency. On the other hand, Niobium pentoxide is an n-type transition metal oxide semiconductor with good chemical stability and a conduction band potential that is 0.2 – 0.4 eV higher than that of TiO$_2$. This potential difference can form an energy barrier at the electrode-electrolyte interface thereby reducing the rate of recombination of photo-injected electrons. Composite metal oxide semiconductor electrodes possess promising properties could enhance the conversion efficiency of dye sensitized solar cells. However, charge recombination at the interfaces still affects the performance of solar cells fabricated from composites. In this work we introduce TiO$_2$ blocking layer on TiO$_2$/Nb$_2$O$_5$ composite photoelectrode to assess its potential application in dye sensitized solar cells. TiO$_2$ compact layers were deposited on FTO glass substrate by spray pyrolysis technique which was subsequently followed by deposition of nanoporous TiO$_2$/Nb$_2$O$_5$ composite layer by screen printing technique. The structural properties of the deposited films were studied by Raman spectroscopy and X-ray diffraction. Optical properties of the films were evaluated using UV-VIS spectrophotometer in wavelength range of 300-1100 nm. SCOUT software was used to determine thickness and to retrieve the optical constants; refractive index $n_f$ and extinction coefficient $k_\lambda$ of TiO$_2$ compact layer. This was done based on the interactive curve fitting using O’Leary-Johnson-Lim (OJL) interband–transition dielectric model together with Drude model. The photovoltaic parameters of the prepared dye sensitized solar cells were evaluated using current density-voltage ($J$-$V$) characterization from which, the best conversion efficiency was attained with 60 nm thick TiO$_2$ compact layer with current density $J_{sc}$ equal to 8.16 mAcm$^{-2}$, open circuit voltage $V_{oc}$ of 0.79 V, fill factor $FF$ of 0.578 and efficiency $\eta$ of 3.39 %. Further, interfacial charge transfer in the cell was studied using electrochemical impedance spectroscopy. Nyquist plots of the device were measured at a DC bias of 0.6 V. For the best performing cell, recombination resistance $R_{rec}$ was 899.36 Ohm.cm$^2$, chemical capacitance $C_{\mu}$=4.3x10$^{-5}$ Fcm$^{-2}$, transport resistance $R_{tr}$ 4.53x10$^{2}$ Ohm.cm$^2$, geometrical capacitance $C_g$=8.82x10$^{-6}$ Fcm$^{-2}$ and recombination resistance $R_{r}$ =10 Ohm.cm$^2$. Charge carrier life time of the solar cells were also determined with the best performing solar cell having charge carrier lifetime of 3.86x10$^{-2}$ s while charge carrier lifetime for solar cell showing lowest efficiency to be 2.50x10$^{-4}$ s.
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LIST OF SYMBOLS

\( \alpha \) Absorption coefficient
\( \lambda \) Wavelength
\( \gamma_v, \gamma_c \) Damping constants of the valence and conduction bands respectively
\( \mu \) Mobility
\( \omega \) Frequency
\( \omega_p \) Plasma frequency
\( \eta \) Conversion efficiency
\( \varepsilon_i \) Dielectric function
\( \varepsilon_0 \) Permittivity of free space
\( \varepsilon_r \) Relative dielectric constant
\( \varepsilon_s \) Static dielectric constant
\( \xi \) Normalized dipole matrix element
\( \sigma \) Defect density
\( \chi \) Ideality factor
\( \phi \) Phase shift
\( \rho_A \) Density of material
\( \Omega_\tau \) Damping constant
\( c_0 \) Speed of light
\( e \) Charge
\( I, I_d, I_{\max} \) External load current, current lost due to recombination, Maximum current,
\( I_{ph}, I_{ph}, I_{sh} \) Photogenerated current, and Current through shunt resistor respectively.
\( I_o \) Incident light intensity
\( I_{\bar{\gamma}} \) Reverse saturation current
\( I(t) \) sinusoidal current
\( J_{CV} \) Joint density of states
$J_{sc}$ Short circuit current density

$K_B$ Boltzmann’s constant

$K_\lambda$ Extinction coefficient

$m^*$ Effective mass of electrons

$m^*_c, m^*_v$ Conduction band and valence band density of state effective mass respectively.

$n$ Charge carrier density

$n_f$ Refractive index

$N_{c0}, N_{v0}$ Conduction band and Valence band density of state prefactors respectively

$O^{2-}$ Oxygen ions

$P_f$ Average film density

$P_m$ Bulk density

$P_{\text{max}}$ Maximum power

$r$ Particle radius

$r_\delta$ Grain size

$R$ Resistance

$R_{\text{rec}}$ Recombination resistance

$R_s, R_{tr}, R_{sh}$ Series resistance, transport resistance and Shunt resistance respectively

$V$ Potential

$V_{\text{max}}$ Maximum voltage

$V_{OC}$ Open circuit voltage

$Z$ Impedance
## LIST OF ABBREVIATIONS

<table>
<thead>
<tr>
<th>Abbreviation</th>
<th>Description</th>
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<tbody>
<tr>
<td>a-Si</td>
<td>Amorphous silicon</td>
</tr>
<tr>
<td>CB</td>
<td>Conduction band</td>
</tr>
<tr>
<td>CBT</td>
<td>Conduction band tail</td>
</tr>
<tr>
<td>CdTe</td>
<td>Cadmium telluride</td>
</tr>
<tr>
<td>CE</td>
<td>Counter electrode</td>
</tr>
<tr>
<td>CIGS</td>
<td>Gallium diselenide</td>
</tr>
<tr>
<td>DOS</td>
<td>Density of state</td>
</tr>
<tr>
<td>DSSC</td>
<td>Dye sensitized solar cell</td>
</tr>
<tr>
<td>eV</td>
<td>Electron volts</td>
</tr>
<tr>
<td>EDXRF</td>
<td>Energy dispersive x-ray fluorescence</td>
</tr>
<tr>
<td>EIS</td>
<td>Electrochemical impedance spectroscopy</td>
</tr>
<tr>
<td>FF</td>
<td>Fill factor</td>
</tr>
<tr>
<td>Fs</td>
<td>Femtoseconds</td>
</tr>
<tr>
<td>FTO</td>
<td>Fluorine tin oxide</td>
</tr>
<tr>
<td>FWHM</td>
<td>Full width at half maximum</td>
</tr>
<tr>
<td>GW</td>
<td>Gigawatts</td>
</tr>
<tr>
<td>ITO</td>
<td>Indium tin oxide</td>
</tr>
<tr>
<td>I-V</td>
<td>Current –voltage</td>
</tr>
<tr>
<td>JDOS</td>
<td>Joint density of states</td>
</tr>
<tr>
<td>ms</td>
<td>Milliseconds</td>
</tr>
<tr>
<td>ns</td>
<td>Nanoseconds</td>
</tr>
<tr>
<td>Nb₂O₅</td>
<td>Niobium (v) oxide</td>
</tr>
<tr>
<td>OJL</td>
<td>O’Leary-Johnson-Lim</td>
</tr>
<tr>
<td>Ps</td>
<td>Picoseconds</td>
</tr>
<tr>
<td>Pt</td>
<td>Platinum</td>
</tr>
<tr>
<td>PV</td>
<td>Photovoltaics</td>
</tr>
<tr>
<td>RC</td>
<td>Resistor-Capacitor</td>
</tr>
<tr>
<td>SEM</td>
<td>Scanning electron microscope</td>
</tr>
<tr>
<td>TCO</td>
<td>Transparent conducting oxide</td>
</tr>
<tr>
<td>TiO₂</td>
<td>Titanium dioxide</td>
</tr>
<tr>
<td>Abbreviation</td>
<td>Full Form</td>
</tr>
<tr>
<td>--------------</td>
<td>-----------------------------------</td>
</tr>
<tr>
<td>TOE</td>
<td>Tons of oil equivalent</td>
</tr>
<tr>
<td>TW</td>
<td>Terawatts</td>
</tr>
<tr>
<td>UV</td>
<td>Ultra-violet</td>
</tr>
<tr>
<td>VB</td>
<td>Valence band</td>
</tr>
<tr>
<td>VBT</td>
<td>Valence band tail</td>
</tr>
<tr>
<td>XRD</td>
<td>X-ray diffraction</td>
</tr>
<tr>
<td>ZnO</td>
<td>Zinc oxide</td>
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</table>
CHAPTER ONE
INTRODUCTION

1.1 Background of the Study

One of the major societal challenges is related to the rise in global energy demand. International Energy Outlook (2017) projects that world energy consumption will rise by 28% between 2015 and 2040, going from 19.2 to 24.6 Terawatts. This increase in future demand and consumption is inevitable since developing countries also strive to have the same living standard as the developed ones. Today, we primarily use fossil fuels to heat and power our homes and fuel our cars. It is convenient to use coal, oil and natural gas to meet our daily needs. However, they are exhaustible and their combustion has resulted in environmental contamination and greenhouse effect. Research and development of renewable energy resources have therefore attracted great attention worldwide to address this problem.

Hydro-power (1114 GW) has been the main major sustainable energy sources for the longest period (Kaunda et al., 2012), however, other renewable sources are likewise being brought to market. These sources include: wind power (539 GW), photovoltaics (402 GW), geothermal power (12.8 GW) and ocean power (0.5 GW) (Renewable Energy Policy Network, 2018).

Of all the sustainable energy sources, solar power is the most promising, perpetual and continually abundant, quiet and versatile to wide variety of uses from several hundred megawatts outdoor power plant that produce both heat and electricity to small off grid systems that can power areas of the rural settlement and dispersed developments. More energy from sunlight strikes the earth in 1 hour than all the energy demanded globally in an entire year (Tverberg, 2012). Figure 1.1 illustrates the solar radiation spectrum for sunlight at the top of the earth’s atmosphere and at the sea level.
Unfortunately, there is immense gap between abundance and exploitation of solar energy. The gap between the abundant solar radiation and its present utilization presents extraordinary challenge to research efforts to develop cost-effective solar cell technologies with ability to convert more sunlight to electricity.

1.2 Photovoltaics (PV)

Photovoltaic effect is a physical and chemical phenomenon in which light energy is converted into electrical energy. A photovoltaic cell is an electrical device that converts the energy of light directly into electricity.

1.2.1 Principles of photovoltaic conversion

All photovoltaic conversions depend on photoelectric effect in which light falling on semiconductor makes an electron-hole pair in it as demonstrated in figure 1.2. Electrons in the valence band (VB) get excited to the conduction band (CB) of the semiconductor upon

Figure 1.1: Solar radiation spectrum for direct sunlight at both the top of the earth’s atmosphere (yellow part) and at the sea level (red region) (https://commons.wikimedia.org/wiki/File:Solar_spectrum_ita.svg, 2008)
absorption of light of energy $h\nu$ thereby creating holes in the valence band. A built-in-potential barrier acts on the excited electrons making it flow through the external load thereby producing current before recombining with the holes in the valence band.

![Diagram of photovoltaic effect](image)

**Figure 1.2:** Typical representation of photovoltaic effect. Electrons in the valence band (VB) get excited to conduction band (CB) of a semiconductor upon absorption of energy $h\nu$ from the sun creating holes $h^+$ in the valence band.

### 1.2.2 Classification of photovoltaic solar cells

Existing photovoltaic solar cells are categorized into three different groups as shown in figure 1.3. The first generation solar cells, otherwise known as conventional or silicon wafer-based cells, are made of crystalline silicon (c-Si) (Aoyama *et al.*, 2017). These types of PV cells are the commercially predominant photovoltaic technology due to their high efficiency and well-established technology.
Currently in the PV market, silicon based solar cells are the dominating technology accounting for 93% of the total PV plant (Andreani et al., 2019). However, Silicon being an indirect semiconductor with low optical absorption efficiency, therefore, Si wafers have to be as thick as over hundred microns to absorb more incident light. In addition to this, high cost of refining and crystallization process of silicon renders this technology highly expensive (Kaur and Singh, 2016). To confront this challenge, solar cells made of very thin photovoltaic materials were developed. This class of thin film solar cells forms the second generation solar cells.

Second generation solar cells also known as thin film solar cells, are made of photovoltaic material that is much thinner than c-Si solar cells. This effectively reduces their manufacturing cost allowing more straightforward production. The materials used are also widely available. They include copper indium gallium diselenide (CIGS), cadmium telluride (CdTe) (Song et al.,
and amorphous silicon (a-Si) (Krasikov et al., 2016). The toxic nature of the materials like cadmium and the scarcity of telluride and indium pose a major challenge to the development of this generation of solar cells. For this reason, this class of solar cell took off slowly even though they offered better material use and potentially faster manufacture. This made room for another generation of solar cells.

Third generation solar cells have frequently been portrayed as developing technologies. In comparison with high-cost conventional silicon solar cells, third generation solar cells are well known as a cost-effective photovoltaic devices because of inexpensive materials and simple fabrication process. They include thin film silicon solar cells (Haug and Ballif, 2015), dye sensitized solar cells (Andualem and Demiss, 2018), polymer based organic solar cells (Mayer et al., 2007) and more recently, pervoskite cells (Ren et al., 2016). The greater part of them has not yet been popularized and is still in the development stage.

Regardless of their low efficiencies and stability issues of the absorber material, a lot of research has kept on investing into third generation solar cell technologies as they promise to be high efficiency solar cells. Figure 1.4 shows efficiencies for the different generation of solar cells. According to Green et al (2018) highly crystalline silicon solar cells have achieved an efficiency of 26 % which is close to the maximum theoretical efficiency limit (31 %) (Carella et al., 2018).
Among the 3rd generation photovoltaics is the dye sensitized solar cell which is based on nature’s principle of photosynthesis. The operation mechanism of dye sensitized solar cells by injection of electrons from photo excited dye molecules to the conduction band of the metal oxide semiconductor dates back to 1960s. O’Regan and Grätzel (1991) reported breakthrough in fabrication of DSSCs using titanium dioxide as the metal semiconductor. Research on these
types of solar cells has advanced at a fast rate and a considerable amount of work has been done
to improve their efficiency from 7% in 1991 to 13% in 2014. However, these efficiencies are still
low to enable DSSCs be introduced to the PV market. Considering the infinite variation in;
material composition, synthesis, layer stacking, architecture and the substrates, DSSCs have the
possibility to attain high efficiency at low cost compared to the first and second generation solar
cells.

One of the very critical components contributing to this low efficiency is the composition of the
metal oxide semiconductor which has not been fully explored. Nanocrystalline TiO$_2$ possess
large surface area that is essential for adsorbing large amounts of dye except that it brings about
many opportunities for recombination of photo-injected electrons which decreases the cell
efficiency.

Modifications to the semiconductor composition have been performed in attempts to enhance
the electron transport and minimize charge recombination. Composite metal oxide
semiconductors for DSSCs have gained much interest because they seek to take advantage of the
best properties of each material that makes up the composite. Wu et al. (2017a) reported a 2.3 %
increase in efficiency of Ag-TiO$_2$ composite dye sensitized solar cell compared to that with pure
TiO$_2$ photoelectrode. In their study, Nguu et al. (2014) obtained a conversion efficiency of 2 %
for TiO$_2$/Nb$_2$O$_5$ composite DSSC. However, a number of important properties of the photoanode
were not investigated in their work.

Three phase contact between transparent conducting oxide, semiconductor metal oxide and
electrolyte in the dye sensitized solar cell play important role in electron transfer and
recombination dynamics. It is in this regard that we sort to introduce a blocking layer so as to
minimize charge recombination taking place at the FTO/electrolyte interface and in addition, optimize the thickness of TiO$_2$ compact layer for DSSC application.

1.3 Statement of the Problem

Composite metal oxide semiconductor electrode has been used in DSSCs due to their promising properties which could enhance the conversion efficiency of the cells. Notably the efficiencies obtained from composite metal oxide semiconductor are still rather low with Nguu et al. (2014) reporting 2% conversion efficiency by using TiO$_2$/Nb$_2$O$_5$ composite as the photoelectrode. These low efficiencies are partly attributed to electron recombination taking place at the FTO/electrolyte interface. In view of the above, there is still a challenge of minimizing charge recombination at the FTO/electrolyte interface. Nicholas et al. (2018) reported an increase in efficiency from 1.31 % to 3.21 % with introduction of TiO$_2$ compact layer for dye sensitized solar cells made up of TiO$_2$ porous layer. To the best of our knowledge, TiO$_2$ blocking layers have not been exploited in fabrication of photoelectrodes with TiO$_2$/Nb$_2$O$_5$ as the porous layer for DSSC application. Therefore we seek to introduce TiO$_2$ compact layer and study its effect on photovoltaic characteristics of TiO$_2$/Nb$_2$O$_5$ composite dye sensitized solar cells.

1.4 Aim of Study

1.4.1 General objective

The main objective of this work was to study the effect of TiO$_2$ compact layers on the P-V characteristics of TiO$_2$/Nb$_2$O$_5$ composite electrode thin films deposited by spray pyrolysis technique.
1.4.2 Specific objectives

The specific objectives of this study were:

1. To deposit TiO$_2$ compact layer on conducting glass substrate by spray pyrolysis technique.

2. To determine the optical and electrical properties of TiO$_2$ compact layer.

3. To investigate the effect of TiO$_2$ compact layer on the overall performance of TiO$_2$/Nb$_2$O$_5$ dye sensitized solar cells.

1.5 Justification and Significance of study

Efforts are continually being undertaken to improve the performance of DSSCs and hence the competitiveness of this technology in the market. Performance of dye sensitized solar cells is measured by several parameters which are current density ($J_{sc}$), open circuit voltage ($V_{oc}$), fill factor ($FF$) and the energy conversion efficiency $\eta$. Since $V_{oc}$ is determined by the potential difference between the redox level of the electrolyte and the flat band potential, higher open circuit voltage can be achieved by using an oxide with a higher flat band potential. Thus photoelectrochemical properties of DSSCs can be improved by tailoring the photo-electrode materials and their microstructure. The flat band potential of Nb$_2$O$_5$ lies slightly higher than that of TiO$_2$ with a correspondingly higher $V_{oc}$ than that of TiO$_2$ electrode (Eguchi et al., 2000). Nb$_2$O$_5$ has a conduction band in the range 0.2 – 0.4 eV higher than that of TiO$_2$ whose band gap value of 3.5 - 3.8 eV. This property makes it suitable for the formation of mixed-particle structure which could improve the electron transport and dye adsorption (Wei et al., 2008). Composite metal oxides for dye sensitized solar cells have gained much interest due to the fact that they tend to take advantage of the best properties in each component that forms the composite.
Compact layers are used to suppress the electron recombination occurring at the interface between electrolyte and the transparent conducting electrode. TiO$_2$ compact layer has been used to improve the performance of DSSCs by minimizing charge recombination in the cell. In this work we introduce a TiO$_2$ compact layer on TiO$_2$/Nb$_2$O$_5$ with an aim of improving the conversion efficiency of the cell.
CHAPTER TWO
LITERATURE REVIEW

2.1 Introduction

In this chapter most of the aspects based on previous work related to the prime focus of the study are put together. It makes a point by description on every segment of DSSCs.

2.2 History of Dye Sensitized Solar Cells

The principle of solar cell operation is based on photovoltaic effect which was first observed in 1839 by Edmond Becquerel while investigating the effect of light on electrode immersed in electrolyte (Fraas, 2014). Selenium semiconductor coated with very thin layer of gold to form the junction was used to fabricate the first solar cell in 1894 by Charles Fritts. Low conversion efficiency of 1% was obtained from this solar cell (Wu et al., 2017b). Successful development of selenium based solar cells was continued and the research extended into new materials for photovoltaic applications.

The idea of layered structured photovoltaic became prevalent when Bell laboratory designed the first practical cell with an efficiency of 6% in 1954 (Rawal et al., 2015). Tributsch (1971) made the first attempt to generate electricity from dye sensitized solar cell with zinc oxide as the semiconductor and chlorophyll as the sensitizer. Incorporation of dye molecules in some wide band gap semiconductor electrodes was a key factor in developing photoelectrochemical solar cells. O’Regan and Grätzel (1991) succeeded for the first time to produce dye sensitized solar cells of 7% efficiency by sensitizing a nanocrystalline TiO₂ film using novel Ru bipyridl complex.
The development of DSSC in 1990s opened up a new horizon and rapidly propelled photovoltaic technology into the era of third generation solar cells. Dye sensitized solar cells have been investigated and considered as the next generation solar cells due to their cost-effectiveness, abundance of raw materials, simple fabrication process and their general good photovoltaic performance with 13% efficiency recorded (Shah et al., 2016).

2.2.1 Transparent conducting electrode

These are electrical conductive materials with relatively high transmittance of light for effective light radiation conversion to electrical energy. The transmittance of the electrodes should ideally be 90% with sheet resistance not more than 10 ohms/square. Various transparent conducting oxides have been used for optoelectronic applications (Karsten et al., 2017).

Commercially employed TCOs are n-type doped wide band gap oxide materials such as indium tin oxide (In\textsubscript{2}O\textsubscript{3}:Sn, ITO) (Ishibashi et al., 1990), doped zinc oxide (ZnO:Al, ZnO:Ga, ZnO:In), fluorine tin oxide (SnO\textsubscript{2}:F, FTO) (Widiyandari et al., 2013) and amorphous indium gallium zinc oxide (InGaZnO\textsubscript{4}, IGZO) (Cho et al., 2018). Indium tin oxide (ITO) has been greatly used due to its high transmittance and promising electrical conductivity (Wang et al., 2013). However, indium which is used in the production of ITO has some disadvantages in terms of cost and production (Sharma et al., 2018). This has led to exploration of other metal oxides having potentially better properties as transparent conducting electrodes that may replace ITO.

ZnO is considered the prime candidate due to its higher conductivity and low cost. It has excellent electrical, optical, mechanical and chemical properties as well as good thermal stability (Park et al., 2013). Murugesan et al. (2018) developed Al-doped zinc oxide layer with enhanced
electrical and optical properties to substitute the ITO films. However, ZnO is more sensitive to oxygen and process control is more difficult.

Currently, fluorine tin oxide (FTO) is the most widely used TCOs as it has superior electrical and optical properties and are also of low cost. It shows high stability, high resistance to physical abrasion, especially when compared to indium tin oxide (ITO) and it is also abundant (Muthukumar et al., 2013). Napi et al. (2016) reported improved efficiency of dye solar cells by enhancing the surface of FTO film.

### 2.2.2 Dye sensitizers

Efficient electron injection from the excited dye to metal oxide semiconductor plays a vital role in dye sensitized solar cells. Dye functions as electron donor upon excitation by the absorbed photons. Several materials have been studied before in attempts to come up with desirable dyes with better properties (Shiratori and Muraguchi, 2012).

Introduction of natural dyes as better replacement to organic dyes opens up a new direction of research in sensitizers. These types of dyes are cost effective, environmental friendly and biodegradable. One of the most widely available group of natural dye is the anthocyanins (Wongcharee et al., 2007). They can easily bind to the surface of metal oxides semiconductors due to the presence of carbonyl and hydroxyl groups in them (Hao et al., 2006). Unfortunately, the overall efficiencies of DSSCs based on natural dyes remains to be low with the best reported efficiency to be 7.6 % (Wang et al., 2008).

Even though the application of organic dyes is limited by their high cost, non-availability and their complex synthesis (Qin and Peng, 2012), much attention has been put on ruthenium based complexes as photo-sanitizers due to their desirable photoelectrochemical properties and high
stability in oxidized state (Kohle et al., 1997). The most commonly used ruthenium polypyridyl complex dyes for DSSCs are N3, N719, N749, and Z907. Much research is focused on improving the polypyridyl ruthenium dyes by bringing changes in their core structure (Nazeeruddin et al., 2001). To further improve the conversion efficiency of Ru-based dye sensitized solar cells, much attention has been put on improving the spectral response of Ru-based dyes from near-IR to the whole range of VIS of the solar spectrum. Qin and Peng (2012) realized 11.9 % conversion efficiency of DSSCs sensitized by Ruthenium (II) based dyes with iodide based dyes absorbed on nanocrystalline TiO₂.

2.2.3 Redox electrolyte

Charge carrier transport between electrodes and dye regeneration after oxidation of its molecule is performed by the electrolyte in the cell. The electrolyte contains a redox couple in an organic matrix. In the recent years, solid electrolytes have found their application in DSSCs because of their high stability and high efficiency. Their use is however limited by some defects such as low charge transfer, high cost and complex preparation process.

Several attempts have been made to find suitable alternative to iodide/triiodide mediators. Such electrolytes are $S/S^{2-}$ and $Co(II/III)$ (Caramori et al., 2016). However, they are prepared in acetonitrile solution with low boiling point thereby limiting use of device at temperatures above the 80 °C, this also leads to instability issues such as short lifetimes and leakage in the device (Zheng et al., 2017). For now, iodide/triiodide ($I^-/I_3^-$) is the commonly used redox electrolyte due to many advantages in high diffusion rate, low cost and ease of preparation (Tseng et al., 2016).
2.2.4 Counter electrode

Counter electrode provides surface that enhances charge collection from the external circuit to the electrolyte and also acts as a catalyst that helps in regeneration of $I^-$ from $I_3^-$. According to these basic functions, an effective counter electrode should have high catalytic activity, low resistivity, high surface area, chemical, electrochemical ad mechanical stability and its energy level that matches the potential of the redox couple electrolyte.

Various materials have been evaluated for use as counter electrodes. The materials that have been investigated include carbon based nanomaterials such as carbon nanotubes (Murakami et al., 2006), carbon soot, graphene, and graphite, inorganic semiconducting chalcogenide compounds such as NiS, CoS and CoSe and platonic composite materials (Roy-Mayhew et al., 2010). These materials possess good electrical conductivity, have large surface area and are cost-effective. Their Production is cheap and they are also widely available (Yang et al., 2013). However, Platinum Pt has consistently been used as a CE since it possesses high electrical conductivity, high catalytic activity and also provides stability against iodine corrosion in the electrolyte and also holds the record of highest conversion efficiency (Calogero et al., 2011).

2.2.5 Metal oxide semiconductors

Metal oxide semiconductors have a major role to play in the performance of dye sensitized solar cells. Titanium dioxide (TiO$_2$), niobium pentoxide (Nb$_2$O$_5$) and zinc oxide (ZnO) are desirable materials exhibiting efficient electron transfer within dye sensitized solar cell depending on their electronic band structure (Kalyanasundaram, 2010).

Nb$_2$O$_5$ thin films were shown to exhibit similar properties as TiCl$_4$ post treated TiO$_2$ thin films (Černá et al., 2011). It has also been shown that thin films of Nb$_2$O$_5$ or ZnO deposited on TiO$_2$
layer reduce charge recombination in DSSC (Kalyanasundaram, 2010). Nb$_2$O$_5$ dye sensitized solar cell with approximate thickness of 2.3 μm has been shown to improve conversion efficiency of the cell by 1.4 % (Kim et al., 2015). It is considered as a suitable alternative to TiO$_2$ (Al-Juaid et al., 2012). However, Nb$_2$O$_5$ is not widely available as TiO$_2$ because of its high demand as pigment in paints (Chen et al., 2001) and UV absorber in the cosmetics industries (Abdul et al., 2014).

Among all the wide band gap semiconductors explored as alternatives to TiO$_2$ as an electron conductor, ZnO presents excellent bulk electron mobility (Look et al., 1998) with a band structure similar to that of TiO$_2$ and also has intriguing optoelectronic features. Yodyingyong et al. (2010) reported a conversion efficiency of 7 % for DSSC based on mesoporous ZnO sensitized with common ruthenium-based dyes prepared under different preparation conditions and electrolyte composition.

However, as a photoelectrode, ZnO has drawbacks such as chemically unstable and is easily dissolved in acidic and basic solutions and the amount of dye loadings is less than that of TiO$_2$. TiO$_2$ is a wide band gap semiconductor existing in three main forms; anatase structure which is formed at lower temperatures and has wide band gap energy of 3.2 – 3.8 eV (Jose et al., 2009a), brookite phase with band gap energy of 3.14 eV, and rutile phase with the least band gap energy 3.06 eV, possessing the highest refractive index and has the most thermodynamically stable structure. Their structure consists of a Ti atom surrounded by 6 oxygen TiO$_2^-$ in a more or less distorted configuration. Figure 2.1 shows the structures for different phases of titanium dioxide. The octahedron in anatase phase are connected by their edges forming a (001), in rutile, by vertices, forming (110) plane and in brookite by both edges and vertices (Diebold, 2003).
Figure 2.1: Crystal structures for anatase, rutile and brookite phase of TiO$_2$ (Fujishima et al., 2008).

TiO$_2$ has been the most successful metal oxide semiconductor used in DSSCs based on its unique properties such as its excellent band alignment with various organic and inorganic dyes, stability, non-toxic, low cost, available in abundance. It is widely used as a semiconductor in DSSCs to produce a high surface area for adsorption of a greater density of dye molecules, which produces a significant increase in the photocurrent (Meng et al., 2010). However, the highly porous structure of TiO$_2$ layer cause recombination of the charge/electrons, which interferes with the unidirectional electron transfer that takes place at the TiO$_2$ layer/dye molecule and FTO/TiO$_2$ layer interfaces (Kim et al., 2012).

Efforts have been made to explore other materials such as composite metal oxide semiconductor in order to improve electron transport and minimized recombination in the cells. Such composites include SnO$_2$/TiO$_2$ (Bak et al., 2011), TiO$_2$/ZrO$_2$ (Wang et al., 2012), ZnO/ZnS (Rouhi et al., 2015), MgO/TiO$_2$ (Wu et al., 2008). Gao et al. (2012) used porous SnO$_2$ nanotube-
TiO\(_2\) (SnO\(_2\) NT-TiO\(_2\)) core shell structured photoanode which yielded a conversion efficiency of 5.11 \% which was five times higher than that of TiO\(_2\) nanoparticles. The conduction band of Nb\(_2\)O\(_5\) is 100 mV negative than that of TiO\(_2\) material. Thus Nb\(_2\)O\(_5\) form an energy barrier to the photoelectrode and therefore confine the electrons to the core of TiO\(_2\) particles. This electron confinement reduces the recombination thereby improving the \(V_{oc}\). More research is still focused on TiO\(_2\)/Nb\(_2\)O\(_5\) composite semiconductor for application in DSSCs though previous studies reported low conversion efficiencies. In this study, photoelectrodes formed by a mixed particle structure are expected to incorporate alteration in conduction band edge in the TiO\(_2\) and Nb\(_2\)O\(_5\) composite thereby yielding high \(V_{oc}\).

2.2.6 **Compact layer**

The nanoporous electrode shows high surface area for light harvesting efficient electron injection. Unfortunately, high electron recombination occurs at the electrolyte/electrode interface for nanoporous electrode due to absence of energy barrier layer (Mebrahtu et al., 2017). Charge transfer kinetics has been the focus of many researches in dye sensitized solar cells (Beek and Janssen, 2004). Effects of linear recombination kinetics that involves electron transfer in TiO\(_2\) to redox couple in the electrolyte have been accounted for by several theoretical works (Bisquert and Mora-Seró, 2010). Recombination of photoelectrons at the interface of transparent conducting oxide/electrolyte is a disadvantageous reaction to efficient energy conversion in dye sensitized solar cells (Augustyniak, 2016).

To address this, compact layer has shown to be an effective alternative method to minimize electron recombination occurring at DSSC interfaces (Peng et al., 2004). Figure 2.2 show a complete dye sensitized solar cell structure without a compact layer with possible recombination
paths and a DSSC with compact layer incorporated in its structure. Recombination of photo-injected electrons with the redox couple is prevented by the physically-blocked FTO/electrolyte interface.

Additionally, compact layer improves the adhesion of porous layer to the conducting glass substrate contact area (Choi et al., 2012). Semiconductors such as TiO$_2$, Nb$_2$O$_5$ (Xia et al., 2007) and ZnO (Roh et al., 2006) have been used as blocking layers in DSSCs which, compared to the unblocked case had a higher photo-voltage and efficiency. Among them, TiO$_2$ is the most suitable candidate material as blocking layer.

Sputtering technique (Waita et al., 2009; Xia et al., 2006) and dip coating methods (Hong et al., 2015) have been employed for the deposition of compact layer. However these techniques are expensive and deposition takes longer time. In this study, we seek to use spray pyrolysis method.

Figure 2. Dye sensitized solar cell (i) without compact layer and (ii) Unidirectional electron transfer through the blocking layer. The three pathways for back reaction of electrons in a DSSC: (a) With the oxidized dye, (b) With the electrolyte via the TiO$_2$, (c) With the electrolyte via FTO substrate.
to prepare blocking TiO$_2$ layer to maximize conversion efficiency of DSSC. This method is of low cost and faster compared to the other techniques.
CHAPTER THREE
THEORETICAL FRAMEWORK

3.1 Introduction
This chapter explains the theoretical aspect of optical properties of thin films and the operation principle of dye sensitized solar cells. Different models in SCOUT software used for determination of the optical constant are also discussed and also given are the fundamental theories on electrochemical impedance spectroscopy.

3.2 Optical Properties and Band gap Evaluation
The theoretical and experimental study of optical behavior of materials is used to obtain the optical constants such as refractive index $n_f$ and extinction coefficient $k_f$ (Bhattacharyya et al., 2009). The intensity of transmitted light through thin film depends on the incident photon wavelength and the material thickness. Taking reflectance of light on the film to be minimal, the intensity of transmitted light is evaluated as follows (Bouabellou, 2013);

$$I = I_o e^{-\alpha d}$$  \hspace{1cm} (3.1a)

$$\alpha d = \ln\left(\frac{I_o}{I}\right)$$  \hspace{1cm} (3.1b)

where, $I$ is the transmitted light intensity, $I_o$ is incident light intensity, $\alpha$ is absorption coefficient and $d$ is the film thickness. Absorption of radiation that leads to electronic transitions between the valence and conduction band is split into direct and indirect transition. Near the absorption edge, the absorption coefficient is expressed as

$$\alpha \approx (\hbar \nu - E_g)^\gamma$$  \hspace{1cm} (3.2)
where $h\nu$ is the photon energy, $E_g$ is band gap energy and $\gamma$ is transition type equals to $\frac{1}{2}$ and 2 for direct and indirect transitions respectively (Hao et al., 2018). The optical band gap can be determined by Tauc’s empirical model and using his equation, the relationship between absorption coefficient $\alpha$ and photon energy $h\nu$ can be established from the equation below (Ting et al., 2000);

$$\left(\frac{\alpha h\nu}{\beta}\right)^{\frac{1}{2}} = \beta (h\nu - E_g) \tag{3.3}$$

where $\beta$ is a constant that depends on the properties of the material. When $\left(\frac{\alpha h\nu}{\beta}\right)^{\frac{1}{2}}$ is plotted against $h\nu$, the tangent intercept gives $E_g$ (Nikolay et al., 2011). The energy by which photon strikes the film surface is given by;

$$E = h\nu, \text{ but } \nu = \frac{c_o}{\lambda}$$

$$E = \frac{hc_o}{\lambda} \tag{3.4}$$

$$E = \frac{1240 \text{ eV.nm}}{\lambda(nm)}$$

Where $\nu$ is the frequency, $h$ is the Plank constant $(6.63\times10^{-34} \text{ J.s})$, $c_o$ speed of light $(3.00\times10^8 \text{ ms}^{-1})$ and $\lambda$ is the wavelength in nanometers. Theoretically obtained direct band gap values of titanium dioxide $(\text{TiO}_2)$, $E_g = 3.2 - 3.9 \text{ eV}$ (Oommen et al., 2013) and $E_g = 3.9 \text{ eV}$ for niobium pentoxide $(\text{Nb}_2\text{O}_5)$ (Jose et al., 2009a).

Theoretical analysis of experimental optical data was used to determine the optical constants of different thin films using various dielectric models. SCOUT software was used for the thin film
analysis by spectrum simulation of reflectance, transmittance, absorbance, ellipsometry, photoluminance and electroluminance. It can also be used to estimate thickness of the films (Theiss, 2000).

### 3.2.1 Drude model

Drude model (1900) is a classical model that assumes both electrons and ions as solid spheres. It is based on the kinetic theory of electrons in a material where assumed that the material has motionless positive ions and non-interacting electron gas (Ortega et al., 2018; Barchiesi and Grosges, 2014). This model links optical and electrical properties of a material with the behavior of its electrons or holes. The model well describes the electronic transition of free charge carriers.

The model has been shown to provide a fair explanation on cases where electrons are considered to have an appreciable interaction with each other and can be used to evaluate the optical properties at energies below the band gap accounting for interband transition of the conduction electrons. The model assumes that an incoming electromagnetic wave of frequency $\omega$ forces damped oscillation of the essential free electron in the semiconductor with damping constant $\Omega$. It involves a typical frequency (plasma frequency $\omega_p$) above which the semiconductor reflectivity decreases. The plasma frequency is given as (Mendoza et al., 2014);

$$\omega_p = \frac{1}{2\pi c_o} \left( \frac{4\pi n e^2}{m^*} \right)^{\frac{1}{2}}$$  \hspace{1cm} (3.5)

where $n$ is the charge carrier density, $m^*$ is effective mass of electrons and $c_o$ is the speed of light.
3.2.2 O’Leary-Johnson-Lim (OJL) model

The O’Leary-Johnson-Lim (OJL) model is used to describe the inter-band transition in semiconductor materials. The interband transitions are depicted by the model that assumes the parabolic shape of the density of state (DOS) function for the valence and the conduction bands with tail states exponentially decaying into the band gap. The shape of the conduction and valence band DOS are mathematically defined as a function of energy, predominantly by the parameters $E_o$ (defining the gap between the band edges), mass (a scaling factor determining the shape of the DOS) and gamma (reflecting the width of the exponential band tails) (Solieman et al., 2014). The fit parameters of the OJL interband transition model are the gap energy, $E_V$ and $E_C$, (the gap between the band edges), the “damping constants” of the valence and conduction bands, $\gamma_V$ and $\gamma_C$ (gives the band tail width), the mass of the transition $m$ (related to the strength of transition) and the decay factor $f$ which drags down the imaginary part to zero at high frequencies (El-Amin and Solieman, 2015). In the OJL model, the refractive index $n_r$ as a function of energy is determined mainly by the parameter ‘mass’, which determines the shape of the conduction and valence band DOS. The empirical equations of DOS functions were adapted to include the transition in each of the DOS functions between the band region and the tail region. That is;

Density of state function for the valence band edge;

$$f_v(E) = \frac{\sqrt{2m_v^*}}{\pi^2h^3} \begin{cases} \sqrt{E_v - E} & E \leq E_v - \frac{1}{2}\gamma_v \\ \frac{1}{\sqrt{2}} - \gamma_v \exp\left(-\frac{1}{2}\right) \exp\left(\frac{E_v - E}{\gamma_v}\right) & E > E_v - \frac{1}{2}\gamma_v \end{cases} \quad (3.6)$$

and density of states for the conduction band edge;
\[ f_c(E) = \frac{\sqrt{2m^*}}{\pi^2\hbar^3} \begin{cases} \sqrt{E - E_c} & \text{if } E \geq E_c + \frac{1}{2} \gamma_c \\ \frac{1}{\sqrt{2} \gamma_c} \exp\left(-\frac{1}{2}\right) \exp\left(\frac{E - E_c}{\gamma_c}\right) & \text{if } E < E_c + \frac{1}{2} \gamma_c \end{cases} \] (3.7)

\( f_v(E) \) and \( f_c(E) \) are the density of states at the valence and conduction band respectively \( m^*_v \) and \( m^*_c \) are the effective masses of density of states at the conduction and valence band respectively. \( E_c \) and \( E_v \) denotes the sharp edges of conduction and valence bands, and \( \gamma_v \) and \( \gamma_c \) are the broadening spreads of valence band tail (VBT) and conduction band tail (CBT) states, respectively (Solieman and Abu-sehly, 2011).

The joint density of states (JDOS) \( J_{CV}(\hbar\omega) \), associated with its broadened conduction and valence band is described by the following general equation (Saleh et al., 2014)

\[ J_{CV}(\hbar\omega) = \int_{-\infty}^{\infty} f_v(E) f_c(E + \hbar\omega) dE \] (3.8)

The product of joint density of state and the oscillator strength yields the imaginary part of the dielectric function as described in the following equation

\[ \varepsilon_i(\hbar\omega) = (\pi e)^2 \left( \frac{4}{3 \rho_A} \right) \xi^2(\hbar\omega) J_{CV}(\hbar\omega) \] (3.9)

Where \( \xi^2(\hbar\omega) \) is the normalized dipole matrix element and \( \rho_A \) the atomic density of material.

The absorption coefficient can be determined by the product of JDOS and the normalized dipole matrix element squared as shown
\[ \alpha(\hbar\omega) = \zeta^2(\hbar\omega) J_{cv}(\hbar\omega) \] (3.10)

### 3.3 Dye Sensitized Solar Cell Operation Principle

Upon irradiation with monochromatic light, the dye molecule on metal oxide semiconductor absorbs the light and gets excited from the ground state \((D)\) at high occupied molecular orbital (HOMO) to the excited state \((D^*)\) at the lowest unoccupied molecular orbital (LUMO), thus emitting photogenerated electrons (Su’ait et al., 2015).

\[ \text{TiO}_2 / D + h\nu \rightarrow \text{TiO}_2 / D^* \] (3.11)

Electron injection into conduction band of large band gap metal oxide semiconductor is caused by dye excitation upon which the dye molecule gets oxidized \((D^+)\).

\[ \text{TiO}_2 / D^* \rightarrow \text{TiO}_2 / D^+ + e^- \] (3.12)

The oxidized dye is regenerated by receiving electron from \(I^-\) redox mediator which is in turn oxidized \(I_3^-\) at the counter electrode with electrons flowing through the external load.

Conversion of light into electricity is the overall outcome of the whole process

\[ \text{TiO}_2 / D^+ + e^- \rightarrow \text{TiO}_2 / D \]
\[ \text{TiO}_2 / D^+ + \frac{3}{2} I^- \rightarrow \text{TiO}_2 / D + \frac{3}{2} I^- : \text{Regeneration} \]
\[ \frac{1}{2} I_3^- + e^- \rightarrow \frac{3}{2} I^- \]
\[ I_3^- + 2e^- \rightarrow 3I^- : \text{Redox reaction} \] (3.13)

Figure 3.1 illustrates the electron kinetics in the dye sensitized solar cells.
The arrows indicate dye excitation from the highest occupied molecular orbital (HOMO) level to lowest unoccupied molecular orbital level, excited state relaxation (60 ns), injection of electrons from lowest unoccupied molecular orbital (LUMO) level of the dye to conduction band of the semiconductor which is approximately 50 fs-1.7 ps, electron recombination with the hole in highest occupied molecular level of dye (ns-ms), charge recombination in conduction band of semiconductor with hole $I_3^-$ in the electrolyte (10 ms) and oxidized dye regeneration by ions (Hara and Arakawa, 2005).

Electron injection kinetics to the conduction band of semiconductor after excitation from photosensitizers has been studied using time-resolved laser spectroscopy (Gan et al., 2007). Efficiency of charge transfer to the semiconductor is greatly affected by photosensitizer configuration and energy separation between conduction band of semiconductor and lowest unoccupied molecular orbital (LUMO) level of the photosensitizer.
Photoelectric conversion processes in DSSCs can be understood through equivalent circuit which provides means to analyze cell devices and improve cell performance. The diode-like behavior in dye sensitized solar cells is as a result of charge transport at the metal oxide semiconductor/dye/electrolyte interface (Han et al., 2004). Series and shunt resistance are included in the circuit to account for various losses mechanism in the device. Figure 3.2 shows one-diode model equivalent circuit for dye sensitized solar cells. The external load current is given as (Zaidi et al., 2018);

\[ I = I_{ph} - I_d - I_{sh} \]  \hspace{1cm} (3.14)

where \( I_{ph} \) is the photogenerated current, \( I_d \) is the voltage dependent current lost to recombination and \( I_{sh} \) is the current lost due to shunt resistance. The diode current is modeled using Shockley equation for an ideal diode as;

\[ I_d = I_\beta \left( \exp \left( \frac{-e(V - IR_s)}{\chi K_B T} \right) - 1 \right) \]  \hspace{1cm} (3.15)

\( I_\beta \) is the diode reverse current, \( \chi \) the ideality factor, \( R_s \) the series resistance, \( K_B \) Boltzmann’s constant (1.38×10^{-23} J/K), \( e \) the elementary charge, \( T \) absolute temperature and \( V \) the potential. The shunt current is given as;

\[ I_{sh} = \frac{V + IR_s}{R_{sh}} \]  \hspace{1cm} (3.16)

\( R_{sh} \) is the shunt resistance. The external load current is therefore expressed as;
\[ I = I_{ph} - I_d \left( \exp \left( \frac{-e(V - IR_s)}{\alpha k_B T} \right) - 1 \right) + \frac{(V - IR_s)}{R_{sh}} \]  

(3.17)

Figure 3.2: One-diode equivalent circuit diagram for dye sensitized solar cells (Ghani and Duke, 2011)

3.3.1 Short circuit photocurrent \((I_{sc})\)

Short circuit current is described as the current that flows between two photoelectrodes and is obtained from solar cell when load resistance is zero and mainly depends on photo-generated electrons and recombination of holes and electrons at the interfaces.

3.3.2 Open circuit potential \((V_{oc})\)

This is the highest voltage achievable from solar cell at a given light intensity. It is the potential at which the current density through the cell is zero \((J_{sc} = 0)\). It can also be expressed as the voltage difference between quasi-Fermi potential of electrons \(\frac{E_{CB}}{e} \) in the conduction band and redox potential of electrolyte \(\frac{E_{redox}}{e} \) (Marinado et al., 2010)
\[ V_{oc} = \frac{E_{CB}}{e} + \beta \gamma \frac{K_B T}{e} \ln \left( \frac{n}{N_{CB}} \right) - \frac{E_{\text{redox}}}{e} \]  

(3.18)

where \( E_{CB} \) is the conduction band edge energy level, \( N_{CB} \) is the total number of conduction band states in the semiconductor, \( n \) is the number of electrons in semiconductor, and \( e \) is the elementary charge of the electrons. For the ideal case (i.e., a defect-free semiconductor material), \( \beta \gamma = 1 \). Porous TiO\(_2\) used in DSSCs often shows a non-ideal relation, \( \beta \gamma \neq 1 \), where the origin might be additional electronic states referred to as trap states.

### 3.3.3 Series and shunt resistance

Series resistance \( (R_s) \) and Shunt resistance \( (R_{sh}) \) in solar cells are major factors affecting the conversion efficiency of the cell. High values of \( (R_s) \) and low \( (R_{sh}) \) lead to decrease in short-circuit current \( (I_{sc}) \) and open-circuit voltage \( (V_{oc}) \) respectively (Singh and Ravindra, 2012). Shunt resistance is caused by leakage current through the cell due to imperfections on the device surface (McIntosh and Honsberg, 2000). Shunt resistance can be obtained by inverse slope near the short circuit current \( I_{sc} \). Low \( R_{sh} \) results in decrease in short circuit current of the cell thereby affecting maximum power output fill factor and the efficiency. Figure 3.3 shows the effect of shunt resistance and series resistance on the \( I-V \) curve. Shunt resistance is not affected by the intensity of illumination (Siddique et al., 2013). Series resistance affects the energy output and fill factor of the cell (Cabestany and Castañer, 1983). Decrease in series resistance lead to improved open circuit voltage of the cells.
3.3.4 Fill factor ($FF$)

This is ratio of maximum generated power to the product of open circuit voltage $V_{oc}$ and short circuit current $I_{sc}$ of a solar cell. For dye sensitized solar cells, it is a parameter used to specify the quality of solar cell by checking the extent of electrical and electrochemical losses in the cells. It is a function of series and shunt resistances of the cell. Shunt resistance should be increased while minimizing series resistance so as to obtain high fill factor of the device.

$$
FF = \frac{I_{max} V_{max}}{I_{sc} V_{oc}} = \frac{P_{max}}{I_{sc} V_{oc}}
$$

(3.19)

where $P_{max}$ is the maximum power generated by the solar cell at voltage $V_{max}$ and current $I_{max}$, $I_{sc}$ is the short circuit current and $V_{oc}$ is the open circuit voltage of the cell.
3.3.5 Power conversion efficiency ($\eta$)

This is the ratio of energy output $P_{\text{max}}$ from solar cell to energy input $P_{\text{in}}$ at the surface of solar cell and it is generally expressed as a percentage.

$$\eta(\%) = \frac{P_{\text{max}}}{P_{\text{in}}} = \frac{V_{\text{max}}I_{\text{max}}FF}{P_{\text{in}}} \times 100\%$$  \hspace{1cm} (3.20)

where $P_{\text{max}}$ is maximum power output, $P_{\text{in}}$ is incident radiation power, $FF$ is fill factor, $V_{\text{max}}$ maximum voltage and $I_{\text{max}}$ maximum current at maximum power output. Figure 3.5 shows the $I-V$ characteristic curve for dye sensitized solar cell.

![Figure 3.4: I-V characteristic curve of dye sensitized solar cells.](image)
3.4 Electrochemical impedance spectroscopy (EIS)

This is a widely used technique for characterization of the electrical properties and operation mechanism of solar cells (Sarker et al., 2014). Impedance is the response of a cell to an applied potential whose frequency reveals the underlying chemical processes (Wang et al., 2006). This technique involves determination of response of an electrode to sinusoidal potential modulation at different frequencies. EIS has been extensively used for determination of charge carrier lifetime under a range of operating biases and illumination intensities.

The main interest is the system response to the application of sinusoidal signal. The measurement is performed under sinusoidal potential modulation with amplitude 0.005 - 0.01 V. Sinusoidal perturbation of potential $E(t)$ induces a sinusoidal current $I(t)$ of the same frequency ($\omega$) superimposed onto the steady state current with phase shift $\phi$ with respect to the potential.

As for physical electric circuits, the electrochemical impedance of the electrode reaction ($Z$) is defined analogous to Ohms’ law as (Lasia, 1999).

$$Z(\omega) = \frac{E(t)}{I(t)} = \frac{|E_o|\sin(\omega t)}{|I_o|\sin(\omega t - \phi)} = Z_o \frac{\sin(\omega t)}{\sin(\omega t - \phi)}$$

(3.21)

Here, $E_o$ and $I_o$ is the amplitude of the potential and current respectively, $\omega = 2\pi f$ is the radial frequency in rads/s.

With the mathematical identity;

$$\exp(jx) = \cos x + j\sin x$$

(3.22)

It is obtained that

$$E(t) = |E_o|\exp(j\omega t) \text{ and } I(t) = |I_o|\exp(j\omega t - j\phi)$$

(3.23)
From equation (3.15), impedance can also be expressed as the sum of real \((Z_{re})\) and imaginary \((Z_{im})\) parts at a given frequency \(\omega\) as given in equation (3.17).

\[
Z(\omega) = |Z_o| \exp(j\phi) = |Z_o| (\cos \phi + j \sin \phi) = |Z_o| \cos \phi + j |Z_o| \sin \phi = Z_{re} + jZ_{im}
\]  

(3.24)

Nyquist plot with the impedance can be represented by a vector (arrow) of length \(|Z|\). The angle between this vector and the x-axis, commonly called the phase angle is \(\phi\) (=arg \(Z\)) as shown in figure 3.5.

![Nyquist plot](image)

**Figure 3.5:** Typical representation of impedance

A sinusoidal voltage applied to an ohmic resistance induces an alternating current that is in phase with applied voltage and the impedance of the ohmic circuit element is therefore equal to its resistance \(R\):

\[
Z_r = \frac{E(t)}{I(t)} = \left| \frac{E_o \sin(\omega t)}{I_o \sin(\omega t)} \right| = R
\]  

(3.25)

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The impedance of the resistor is independent of frequency and has no imaginary component. The impedance of a capacitor can be calculated based on the relation

\[ I(t) = C \frac{dE(t)}{dt} \]  

That yields the expression of capacitance impedance, its modulus and phase shift.

\[ Z_c = -\frac{j}{\omega C}, \quad |Z_c| = \frac{1}{\omega C}, \quad \text{and} \quad \phi = -\frac{\pi}{2} \]  

The real and the imaginary parts of the impedance are related to phase angle \( \theta \) as

\[ \theta = \tan^{-1} \left( \frac{Z''}{Z'} \right) \]  

And magnitude \( |Z| \) as

\[ |Z| = \sqrt{Z'^2 + Z''^2} \]  

The operation of solar cell is governed by two competing processes. On one hand, photoexcitation and electron injection into the conduction band of the large band gap semiconductor which leads to creation of current that flows towards the external load. The other process involves recombination of the injected electrons thereby internally annihilating the moving carriers (Bisquert et al., 2009).

Due to the complex nature of real devices, equivalent circuits are used to simulate the impedance behavior of such devices. These equivalent circuits ought to be complex enough to show approximately the same impedance characteristics as the real devices and at the same time simple for easy analysis (Krogmeier, 2016). The roles of internal cell surfaces as well as device
components have been studied by equivalent circuit element. Figure 3.6 shows a typical representation of an equivalent circuit dye sensitized solar cell.

$$R_{TCO}$$ is a charge-transfer resistance for electron recombination from the uncovered layer of the TCO to the electrolyte, $$C_{TCO}$$ double layer capacitance at exposed transparent conducting oxide (TCO)/electrolyte interface; $$Z_{d(sol)}$$ is the Nernst diffusion of $$I^-_3$$ in the electrolyte, $$R_{pt}$$ is the charge-transfer resistance at the counter electrode/electrolyte interface and $$C_{pt}$$ is the double layer capacitance at the counter electrode/electrolyte interface. $$R_{CO}$$ and $$C_{CO}$$ are the resistance and the capacitance at TCO/TiO$_2$ contact, $$C_{\mu}$$ is the chemical capacitance of the TiO$_2$ film, $$R_{ctTiO_2}$$ is the transport resistance of electrons in TiO$_2$ film and $$R_{sTCO}$$ is the series resistance in the transparent conducting electrode.

Chemical capacitance is the measure of readiness for stoichiometric changes and it describes the electro-neutral chemical storage of charges. It is described as (Leever et al., 2012);
\[ C_\mu = e^2 \frac{\partial N}{\partial E_{fn}} = e^2 \frac{N}{k_B T} \]  

(3.30)

\( C_\mu \) is the chemical capacitance per unit volume, \( e \) is the elementary charge, \( N \) is the electron contribution and \( E_{fn} \) is the quasi-Fermi level generated by excess electrons in the acceptor.

Recombination resistance \( R_{\text{rec}} \) is introduced as part of the equivalent circuit. It is related to the recombination current density \( J_{\text{rec}} \) following the expression (Garcia-Belmonte et al., 2010);

\[ R_{\text{rec}} = \frac{1}{A} \left( \frac{dJ_{\text{rec}}}{dV_{oc}} \right)^{-1} \]  

(3.31)

where \( A \) is the device area.
CHAPTER FOUR
MATERIALS AND METHODS

4.1 Introduction

In this chapter, appropriate experimental details of preparation of the dye sensitized solar cell, TiO$_2$/Nb$_2$O$_5$ composite thin film characterization and analysis employed in this work are described. The chapter details the techniques by which TiO$_2$ compact layer and TiO$_2$/Nb$_2$O$_5$ composite thin films were prepared.

4.2 Fabrication of the Photoanode

Prior to deposition of TiO$_2$ compact layer, the FTO substrates were cleaned in steps as outlined below. A gross cleaning process was performed to get rid of large amounts of contaminant off the surface of the substrates. This as achieved by scrubbing the surface of the substrates using cotton bud dipped in a solution containing a mixture of sodium hydroxide, detergent and deionized water. To further remove specific contaminants such as oils or organic residue off the surface of the substrates, solvents were used. Unfortunately, solvents themselves (acetone) leave their own residue on the surface of the substrates. This is why three solvents were used. For vigorous cleaning, the substrates were agitated in ultrasonic bath for fifteen minutes at each step to ensure that every spot on the surface of the substrate was cleaned. The substrates soaked in acetone were agitated in ultrasonic bath after which they were soaked in ethanol and agitated once more and finally the substrates were soaked in deionized water before drying. The cleaned substrates were then left to dry in open air for 30 minutes before being used for deposition of the thin films.
4.2.1 Spray pyrolysis

500 µl of commercial titanium (IV) isopropoxide (TiCl$_4$H$_2$O$_4$) (99.7% pure, Aldrich) and 100 ml 2-propanol (C$_2$H$_6$O) (99.5%, Aldrich) were mixed in a 500 ml beaker. To maintain a homogenous mixture, magnetic stirrer was used to mix the content at a constant temperature of 35 °C for about 45 minutes. This solution formed the precursor which was atomized by the spray system using compressed air as the carrier gas (Holmarc, Optomechatronics PVT. Ltd). The setup used is shown in Figure 4.1

![Figure 4.1: Schematic diagram for spray pyrolysis technique](image)

FTO glass substrates (20 mm x 20 mm x 1mm) were mounted on the heating plate and preheated to 200 °C before deposition. Preheating the substrates enables every droplet to undergo pyrolytic (endothermic) decomposition and form single crystal or a cluster of crystallites as a product. The hot substrate surface provides thermal energy for thermal decomposition and subsequent recombination of the constituent species resulting to formation of film. The distance between the substrate and the spraying nozzle was set at 100 mm followed by 150 mm. Spraying was done in pulses, each pulse consisting of 5 seconds of spraying and 30 seconds of pause, at a precursor
flow rate of 2.0 ml/min. The chemical reaction resulting in the formation of amorphous TiO$_2$ thin film was as follows:

$$TiC_{12}H_{28}O_{34(aq)} + 17O_{2(g)} + 2C_{2}H_{2}O_{(aq)} \cdot T\left(100 \, ^{\circ}C - 200 \, ^{\circ}C\right) \rightarrow TiO_{2(s)} \, (amorph) + 8CO_{2(g)} + H_2O_{(g)}$$ (4.1)

The deposited TiO$_2$ thin layers were then annealed in an open air furnace (Jlabtech) step wise at 500 °C for one hour to ensure complete crystallization of the film.

### 4.2.2 Compact layers with varying thickness deposited by spray pyrolysis

In order to deposit compact layer with different thickness, substrate-nozzle distance was set at 100 mm and 150 mm and deposition time also varied from 60 seconds to 120 seconds for each deposition distance. The substrate temperature was kept constant at 200 °C. The deposited films were then annealed and subjected to optical characterization where transmittance was measured using UV- VIS spectrophotometer (Perkin Elmer Lambda 25) in the wavelength range 200 < $\lambda$ < 1100 nm. Thickness of the films was determined using Scout software.

### 4.3 Preparation of Porous TiO$_2$/Nb$_2$O$_5$ Composite Thin Films by Screen Printing Technique

Optimization of the mixing ratios of TiO$_2$ and Nb$_2$O$_5$ powders used in the formation of TiO$_2$/Nb$_2$O$_5$ composite is described in this section. Commercially acquired TiO$_2$ powder (CAS NO: 13463-67-7, Aldrich) and (Nb$_2$O$_5$) nanopowder (CAS NO: 1313-96-8, Acros Organics BCBA, Belgium) were used for the formation of porous TiO$_2$/Nb$_2$O$_5$ composite thin films. Varying ratios of the two powders were mixed with 2 ml of 2-propanol (IPA: isopropyl alcohol, Scharlan Chamia) and 2 ml of deionized water. Nano-particles of the two powders were mixed by increasing the proportion by mass of Nb$_2$O$_5$ from (0.1 to 0.9 g) while decreasing the proportion of TiO$_2$ (from 0.9 to 0.1 g).
Thin TiO$_2$/Nb$_2$O$_5$ composite layers with were coated on FTO glass substrate using screen printing mesh (63T, silk screen printing services LTD, USA). The films were then dried in air at ambient temperature for 10 minutes, transferred to a hot plate at 120 °C for five minutes and allowed to cool to room temperature before sintering stepwise at 500 °C for one hour in a tube furnace. Figure 4.2 shows the deposition of TiO$_2$/Nb$_2$O$_5$ composite thin film by screen printing technique.

![Figure 4.2: Schematic diagram for deposition of TiO$_2$/Nb$_2$O$_5$ composite thin film by screen printing technique](image)

4.4 Thin Film Characterization

To compare the optical characteristics of the deposited TiO$_2$ compact layers, both the optical transmittance ($T$) and absorption ($A$) were measured in the wavelength range 300 -1100 nm (UV-VIS range) on a computerized double beam spectrophotometer (Perkin Elmer Lambda 25). Using the experimentally obtained optical transmittance data in SCOUT 4.06 software, optical constants such refractive index $n_f$ and extinction coefficient $k_\alpha$ and thickness of the samples
were obtained. Drude and OJL dielectric function models were used to give best fitting results for the optical spectra of semiconductor and metal oxide structure (El-Amin and Solieman, 2015). These functions were used to describe the fit parameters for the optical data of TiO$_2$ compact layer and TiO$_2$/Nb$_2$O$_5$ porous layers. In order to determine the optical band gap of the films, the absorption coefficient $\alpha$ obtained from the simulated data in SCOUT software was plotted in Tauc plot as discussed in section 3.2 of chapter 3, where the direct band gap was determined by extrapolating the linear section of the curve to zero. Electrical properties of the films were evaluated using Drude’s parameters; plasma frequency $\Omega_p$ and damping constant $\Omega_\gamma$.

4.5 TiO$_2$/Nb$_2$O$_5$ Elemental Analysis using EDXRF Spectrometer

In this study, energy dispersive X-ray fluorescence spectrometer Shimadzu series EDX-800HS, model CE (212-23701-36), was used to determine the amounts of Ti and Nb composition in the samples. The spectrometer consisted of the following:

i. X-ray generator unit consists of an air cooled of X-ray tube with Rh target operated at 5-50 kV, tube current 0.001-1 mA; primary X-ray filters, automatically switched with an exposure area of 10mm in diameter – four settings 1, 3, 5 and 10 diameters are available for automatic switching.

ii. Semi-conductor Si (Li) detector 10 mm$^2$ mounted at 45 $^\circ$ take-off angle geometry with respect to the sample. It is cooled by liquid nitrogen only during measurement with approximate consumption of 1 liter per day. The detector is biased with a high voltage supply at 50 kV and is connected to a pre-amplifier. The detector measured resolution of about 140 eV for Mn $K\alpha$ at 5.9 KeV.
To determine the elemental composition of the samples, screen-printed TiO$_2$/Nb$_2$O$_5$ composite thin films were analyzed for 50 sec and 100 sec. The elements of interest, Ti and Nb were analyzed following sample irradiation with Rh-tube source. The characteristic fluorescence irradiation of the elements was detected with Si (Li) detector. Figure 4.3 shows the energy dispersive X-ray fluorescence set up used for the analysis of the prepared thin films.

![Diagram](image)

**Figure 4.3:** Schematic diagram of energy dispersive x-ray fluorescence set up

### 4.6 Raman Spectroscopy

Raman spectra are extremely helpful for phase identification with TiO$_2$. Both anatase and rutile are composed of octahedral molecular geometry with the same (TiO$_2$)$_8$. However, the arrangement and distribution are not the same because the connection of their two octahedral structures is different. So, they belong to two different space groups. As such, they have their own characteristic peaks in Raman spectrum (Ohsaka et al., 1978).
Raman spectroscopy was performed to determine the phases of TiO$_2$ present in the films. The Raman spectra were recorded in a back-scattering geometry using a Raman spectrometer (STR Raman, CORNES Technologies Ltd, Tokyo). During acquisition of Raman spectra, an exposure time of 10 seconds was used as per the optimized conditions. A confocal microscope with 100x objective eye piece lens with laser power of 8.52 mW for 785 nm laser was used for measurement. Different films were characterized by taking several Raman spectra at random positions on each film with an area of 0.56 cm$^2$.

### 4.7 Electrical Characterization

The sheet resistivity of the films was determined using four point probe (JANDEL) interfaced with Keithley 2400 source meter. In a four point probe, all the four probes are in a straight line as shown in figure 4.4. A calibrated constant current of source 4.53 mA was passed through the outer probes. Measurements were taken by pressing the four-point probe to the surface of the films. A source current was then activated and the sheet resistance values displayed by the Keithley meter.

![Figure 4.4: Illustration of four-point probe. The inner probes for measuring voltage and the outer probes measuring current.](image-url)
SCOUT software was also used to validate the measurements obtained from four point probe. Electrical properties were analyzed by use of the Drude model based on transmittance data obtained from the *UV-VIS* spectrophotometer. The response of free carriers to the oscillating electric field was described, to a good approximation, by the Drude model. It is a free electron contribution model which describes the intraband contributions to the optical properties. The model has two adjustable parameters; plasma frequency $\omega_p$ and damping constant $\Omega_\tau$.

The parameters of the model relate the concentration of the charge carriers and their mobility to properties of the dielectric function. After a model parameter fit of the simulated spectrum and measured data, the carrier concentration and resistivity was computed. The Drude model relates the macroscopic susceptibility to microscopic quantities carrier concentration $n$, mobility $\mu$ and resistivity $\rho$ by the following expressions (Maghanga and Mwamburi, 2018; Jayasinghe et al., 2012).

\[
n = \frac{4\pi^2 e c O_m^*}{e^2 \omega_p^2} = 3.35 \times 10^{14} \text{ cm}^{-1} \omega_p^2 \quad (4.2)
\]

\[
\mu = \frac{e}{m c O_\tau} = 1.96 \times 10^3 \frac{1}{\Omega_\tau} \quad (4.3)
\]

\[
\rho = \frac{\Omega_\tau}{2\pi c_0 e_o \omega_p^2} = 6.0 \times 10^4 \Omega_\tau \frac{\Omega_\tau}{\omega_p^2} \quad (4.4)
\]

In the above equations, $e$ is the elementary charge ($1.6 \times 10^{-12}$C), $c_0$ is the speed of light in vacuum, $e_o$ is permittivity of free space ($8.854 \times 10^{-12}$ As/Vm) and $m^*$ is the effective mass of charge carriers ($m = 0.3 m_e$), $m_e$ is the mass of an electron, $\Omega_\tau$ is the damping constant and $\omega_p$ is
the plasma frequency. Sheet resistance \( R_{\text{cl}} \) of the films was obtained by using the following equation;

\[
R_{\text{cl}} = \frac{\rho}{d}
\]  

(4.5)

Where \( \rho \) is the resistivity and \( d \) is the film thickness.

4.8 Morphological and Structural Characterization

Scanning electron microscope (SEM) (ZEISS ULTRA PLUS FEG SEM-Microscopes) was used to study the surface morphologies of the deposited thin films. The films were characterized without any further treatment before the scanning was performed. Micrograph images were taken at a constant acceleration potential of 5 kV.

X-ray diffraction (XRD) was performed to identify the crystal structure and the preferred orientation growth of the thin films. This was carried out on Bruker D2 PHASER diffractometer with CuK\(_{\alpha}\) X-ray radiation (1.5418 Å) and readings were taken over the \( 10^\circ < 2\theta < 80^\circ \) range at a scan speed of 0.6 °/s and steps of 0.01 °.

4.9 Preparation of the Electrodes, Counter Electrodes and DSSC Assembly

Subsequent to the formation of the dense and the porous layers of the anode, the thin films were chemisorbed with the dye and used to assemble the DSSC. Preparation of the dye, electrolyte and the counter-electrode was as follows: A synthetic ruthenium-dye (N-719) solution of 0.5 mM was prepared by dissolving 6 mg of Ru-719 in 10 ml of ethanol and sonicated for thorough mixing. The formed thin films were preheated to 200 °C for 15 minutes to get rid of adsorbed water. This was then followed by scrapping some parts to form an active area of 0.56 cm\(^2\).
The films were immersed into the dye solution immediately after heating to prevent re-adsorption of water. The films were soaked for 24 hours to enable proper dye chemisorption. The photoelectrodes were thereafter rinsed with ethanol to detach the excess/unabsorbed dye molecules after which they were immediately used as the photoanode.

4.9.1 Counter Electrode
Pre-drilled FTO glass substrates were cleaned following the procedure outlined in section 4.2. The glass substrates were then dried in open air and platinum (Platisol T/SP Solaronix SA, Switzerland) was coated on the pre-drilled FTO glass substrate and heated in tube furnace at 450 °C for 45 minutes. The counter electrodes were then cooled in dry air before use.

4.9.2 Solar Cell Assembly
The photoanode was prepared as follows: TiO$_2$/Nb$_2$O$_5$ composite coated on TiO$_2$ compact layer were sintered at 200 °C to eliminate absorbed water then the films let to cool to 80 °C. The films were immediately dipped in ruthenium dye complex (N719) that was at room temperature for 24 hours. The dye sensitized films were subsequently rinsed in ethanol to eliminate any excess dye and dried on a hot plate for 10 minutes at 70 °C. Figure 4.4 shows the assembled dye sensitized solar cell.
The photoelectrodes were then fused together with the counter electrode in sandwich manner with 60 μm thick thermoplastic sealing film made of surlyn (Solaronix, Switzerland) applying mechanical pressure at a temperature of 100 °C. Iodide/tri-iodide electrolyte was dropped onto the hole in the counter electrode and injected into the cell by vac ‘n’ fill syringe.

4.10 Current-Voltage (I-V) Characterization of the Solar Cell

Current-voltage (I-V) characteristic were obtained using a set-up consisting of a 500 W xenon lamp, a solar simulator model SS (Science Tech, Canada) equipped with a 1.5 AM filter interphased with a Keithley 2400 (Keithley Inc, USA) source meter controlled by a computer. The measurements were carried out under the intensity of 1000 Wm⁻² (AM 1.5) at the surface of the solar cell. The solar cells had active area of 0.56 cm².

4.11 Electrochemical Impedance Spectroscopy (EIS)

Figure 4.5 shows the setup for electrochemical impedance spectroscopy measurement of the DSSCs. The measurement was performed using potentiostat (AUTOLAB, PGSTAT 204). The cells were illuminated with red light (λ = 627 nm) and spectra obtained under 0.1 sun illumination with varying bias voltage between 0.5 – 0.70 V.
In this study, the impedance was measured at frequency range of 100 kHz – 0.1 Hz. The impedance data obtained from the potentiostat was then analyzed in Matlab software. The function ZfitGUI obtained from (Dellis, 2018) was used to plot and fit the data. Equivalent circuit was as well defined in the Matlab software.

The starting parameters were picked for the fitting process. The value of recombination resistance was estimated by taking the diameter of Nyquist plot semicircles. The starting value for chemical capacitance was set to $10^8 \text{ Fcm}^{-2}$ while the geometrical capacitance was set to a constant value calculated from the cell thickness using equation (Govindasamy et al., 2016).

\[
C_g = \frac{\varepsilon_\text{o}, \varepsilon_r, A}{d} \tag{4.6}
\]

where $\varepsilon_\text{o}$ is the dielectric constant of vacuum, $\varepsilon_r$ is the relative dielectric constant, $A$ is the area of the cell and $d$ is the thickness of the cell.
CHAPTER FIVE
RESULTS AND DISCUSSIONS

5.1 Introduction

In this Chapter, the results obtained from TiO$_2$ compact layer and TiO$_2$/Nb$_2$O$_5$ composite thin film and solar cells fabricated from these films are presented. Optical, electrical and structural properties of TiO$_2$/Nb$_2$O$_5$ composite are discussed. Current-voltage characteristics of solar cells fabricated with and without blocking layers are also presented.

5.2 Structural Characterization of TiO$_2$ Compact Layer and TiO$_2$/Nb$_2$O$_5$ Composite Layer

5.2.1 Analysis of Raman spectra

Raman spectra of TiO$_2$ films deposited by spray pyrolysis technique with the substrate temperature at 200 °C and annealed at 500 °C for one hour is shown in figure 5.1. The spectra in the range of 50 -700 cm$^{-1}$ show five allowed bands at 143 cm$^{-1}$ ($E_{og}$), 196 cm$^{-1}$ ($E_{og}$), 396 cm$^{-1}$ ($B_{1g}$), 504 cm$^{-1}$ ($B_{1g}$) and 637 cm$^{-1}$ ($E_{og}$) respectively for annealed films. These peaks are identical with the features of anatase phase as also reported by Kamran (2014). The peaks were similar for the annealed films regardless of the thickness. The observed Raman peaks are as a result of molecular bond vibrations, that is, vibration mode $E_{og}$ and $B_{1g}$ peaks which are related to different crystal planes These observed peaks confirms the presence of anatase phase of TiO$_2$ thin films (León et al., 2017). All the samples showed a low frequency peak at 143 cm$^{-1}$ which is a typical O-Ti-O bending and is a characteristic feature of the anatase phase (Raut et al., 2009). It can therefore be deduced that phase transition from amorphous to crystalline occurred during the deposition.
Figure 5.1: Raman spectra of as-deposited and annealed TiO₂ compact layer of thickness of 60 nm and 78 nm.

These vibrations are as a result of the presence of anatase phase. In this study, it was observed that the peak position of the TiO₂ anatase Raman bands located at around 196 cm⁻¹ at the high frequency side of the $E_{og}$ mode which can also be assigned as the $E_{og}$ mode of anatase phase. Similar observations were reported by León et al. (2017).

Figure 5.2 shows X-ray diffraction (XRD) pattern of as-deposited and annealed TiO₂ compact layers deposited on FTO substrate at substrate temperature of 200 °C. Peak assignment of the TiO₂ films was done using international center for diffraction data card number 74-1940 (JCPDS). Distinct peaks were observed in all the samples pointing to the nature of crystallinity of the films. The peaks at 27 ° (101), 38 ° (112) and 62 ° (204) obtained in both samples are characteristic crystallographic planes of anatase phase of TiO₂ (Ayieko et al., 2012). As observed, annealed thin films exhibited intense peaks suggesting better crystalline nature and more anatase content in the sample compared to as-deposited thin films.
The spectra for all the samples showed good crystallinity with changes in film thickness showing very little effect on crystallinity. The as-deposited samples also showed good crystallinity with no significance difference with the annealed samples. It can therefore be said that crystallization occurred during the deposition process.

![XRD spectra for as-deposited and annealed spray pyrolysis coated TiO$_2$ layer. The peaks are designated with the reflections of the anatase (A) phase; also indicated are the peaks SnO$_2$:F substrate.](image)

**Figure 5.2:** XRD spectra for as-deposited and annealed spray pyrolysis coated TiO$_2$ layer. The peaks are designated with the reflections of the anatase (A) phase; also indicated are the peaks SnO$_2$:F substrate.

The grain size, $r_g$, of TiO$_2$ thin films was determined using Debye-Scherrer’s formula from the full width at half maximum (FWHM) of the diffraction peaks expressed in radians as follows (Arunachalam *et al.*, 2015).

$$
r_g = \frac{k_{sch} \lambda}{\beta \cos \theta}
$$

(5.1)

where $\lambda = 0.154$ nm is the wavelength of X-ray radiation used, $k_{sch}$ is the Scherrer’s constant (shape factor) ranging from 0.9 to 1.0, $\theta$ is Bragg diffraction angle of XRD peak and $\beta$ is the
FWHM measured from the major (101) crystalline plane. Figure 5.3 shows the Gaussian fit for the major (101) peaks performed using Origin software.

![Gaussian fit for (101) peaks](image)

**Figure 5.3:** Gaussian fit for (101) peaks used for the determination of full width at half maximum (FWHM).

The grain size obtained was 18.59 nm and 19.76 nm for as-deposited and annealed thin films respectively. Increase in crystal size was observed for annealed thin films. Annealing results into reduction of surface energy which is a driving force for grain boundary enlargement and consequently leading to increase in particle size. It also facilitates the movement of atoms or molecules through the mechanism of mass transport that may be lattice diffusion or surface diffusion resulting into grain growth (Sönmezoğlu et al., 2012).

Additionally, to get more information about the amount of defects in the films, the defects related to grain boundary density was determined using equation (5.2). Defect density $\sigma$ in the films is given as the reciprocal of the square of grain size and it is estimated from the following relation using simple approach of (Williamson and Smallman, 1956).
\[ \sigma = \frac{1}{r_0^2} \]  

(5.2)

The defect density obtained was \(2.89 \times 10^{-2} \text{ Å}^{-2}\) and \(2.56 \times 10^{-2} \text{ Å}^{-2}\) for as-deposited TiO\(_2\) compact layer and annealed TiO\(_2\) compact layer respectively. It is seen that the defect density of TiO\(_2\) compact layer decrease with annealing thereby improving the crystallininty of the film (Kose et al., 2009).

Figure 5.4 shows the XRD patterns for TiO\(_2\)/Nb\(_2\)O\(_5\) composite film and TiO\(_2\) porous layer deposited on FTO glass substrate by screen-printing technique. Niobium peaks observed in the diffractograms was assigned using JCPDS card number 28-0317. Crystalline phases of both TiO\(_2\) and Nb\(_2\)O\(_5\) corresponding to diffraction peaks 27.33 ° (101), 38.53 ° (112) 62.22 ° (204) and 46.09 ° (002), 55.01° (102) and 56.72 ° (200) respectively were observed. Most intense peaks for TiO\(_2\) and Nb\(_2\)O\(_5\) are observed at 2\(\theta\) = (27.33 °) and 2\(\theta\) = (54.94 °) respectively. As observed, titanium dioxide tends to have more intense peaks compared to niobium (V) oxide.

**Figure 5.4:** XRD spectra for TiO\(_2\)/Nb\(_2\)O\(_5\) composite layer and pure TiO\(_2\) thin film deposited by screen-printing.
5.3 Energy Dispersive X-ray Fluorescence of TiO$_2$/Nb$_2$O$_5$ Composite Thin Films

Quantitative thin film analysis of the composite with varying ratios of Nb$_2$O$_5$ and TiO$_2$ was achieved using a continuous X-ray beam. Table 5.1 shows various composition in parts per million (PPM) of Nb and Ti contents in the composites as obtained from EDXRF analysis. As observed from the table, as the composition by mass of niobium is increased in the samples so does the parts per million as detected by EDXRF. This is true for concentration by mass of titanium, as the concentration is reduced in the samples o does the values of parts per million.

<table>
<thead>
<tr>
<th>Ratio (in gm) (TiO$_2$:Nb$_2$O$_5$)</th>
<th>Ti (PPM)</th>
<th>Nb (PPM)</th>
</tr>
</thead>
<tbody>
<tr>
<td>0.9:0.1</td>
<td>90800</td>
<td>13900</td>
</tr>
<tr>
<td>0.8:0.2</td>
<td>50800</td>
<td>29600</td>
</tr>
<tr>
<td>0.7:0.3</td>
<td>71000</td>
<td>12300</td>
</tr>
<tr>
<td>0.6:0.4</td>
<td>36400</td>
<td>43100</td>
</tr>
<tr>
<td>0.4:0.6</td>
<td>8200</td>
<td>29600</td>
</tr>
<tr>
<td>0.3:0.7</td>
<td>9920</td>
<td>51500</td>
</tr>
<tr>
<td>0.2:0.8</td>
<td>8540</td>
<td>67700</td>
</tr>
<tr>
<td>0.1:0.9</td>
<td>11800</td>
<td>123000</td>
</tr>
</tbody>
</table>

Shown in figure (5.5) is the EDXRF spectra for films with 20% Nb$_2$O$_5$ and 80% Nb$_2$O$_5$ concentration. All the peaks detected in the scan and their corresponding energy shells from different elements are shown. The analysis revealed higher Nb$_2$O$_5$ intensity for composite film made of 80% Nb$_2$O$_5$ in the composite and a higher TiO$_2$ intensity for 20% Nb$_2$O$_5$ composition in the composite.
Figure 5.5: EDXRF energy spectrum of TiO₂/Nb₂O₅ composite thin film with 20% and 80% Nb₂O₅ content.

5.4 Optical Characterization

The experimental data for transmittance was obtained directly from UV – VIS spectrophotometer (Perkin Elmer Lambda 25) and plotted using Origin Pro 9.1. The effect of annealing and thickness of compact layer on the optical transmittance (T), band gap energy (E₉), refractive index \( n_f \) and extinction coefficient \( k_\lambda \) is discussed. Thickness of the films was determined using scout software. Thickness of the films was mainly influenced by three factors, which are; nozzle-substrate distance, the deposition time and annealing as indicated in table 5.2
Table 5.2: TiO$_2$ compact layers deposited with varying parameters. Annealing was done at 500 °C for one hour

<table>
<thead>
<tr>
<th>nozzle-substrate distance</th>
<th>Deposition time</th>
<th>Treatment</th>
<th>Thickness (nm)</th>
</tr>
</thead>
<tbody>
<tr>
<td>100 mm</td>
<td>60 sec</td>
<td>As-deposited</td>
<td>103 nm</td>
</tr>
<tr>
<td>100 mm</td>
<td>60 sec</td>
<td>Annealed</td>
<td>96 nm</td>
</tr>
<tr>
<td>100 mm</td>
<td>120 sec</td>
<td>As-deposited</td>
<td>125 nm</td>
</tr>
<tr>
<td>100 mm</td>
<td>120 sec</td>
<td>Annealed</td>
<td>120 nm</td>
</tr>
<tr>
<td>150 mm</td>
<td>60 sec</td>
<td>As-deposited</td>
<td>67 nm</td>
</tr>
<tr>
<td>150 mm</td>
<td>60 sec</td>
<td>Annealed</td>
<td>60 nm</td>
</tr>
<tr>
<td>150 mm</td>
<td>120 sec</td>
<td>As-deposited</td>
<td>84 nm</td>
</tr>
<tr>
<td>150 mm</td>
<td>120 sec</td>
<td>Annealed</td>
<td>78 nm</td>
</tr>
</tbody>
</table>

5.4.1 Effects of annealing and film thickness on optical properties of TiO$_2$ compact layer

Transmittance spectra for as-deposited and annealed TiO$_2$ thin layers of different thickness are presented in figure 5.6. A gradual increase in transmittance with increase in wavelength from 350 nm – 600 nm was observed for both as-deposited and annealed films. It was noted that annealed thin films generally exhibited lower transmittance compared to as-deposited thin films. This decrease in transmittance mainly results from light scattering effect which is due to the improved crystallinity of the films (Muaz et al., 2016).
Figure 5.6: Optical transmittance spectra for as-deposited (67 nm thick) and annealed TiO$_2$ compact layers of thickness 60 nm, 78 nm and 96 nm deposited by spray pyrolysis technique.

Transmittance ($T$) is seen to decrease with increase in film thickness. This observation is expected based on Beer-Lambert law equation as shown (Swinehart, 1962):

$$A = -\log_{10}\frac{I}{I_o}$$  \hspace{1cm} (5.3)

Where $A$ is the absorbance, $I_o$ is the incident intensity and $I$ the transmitted intensity.

Due to regular arrangement of the particles and the large surface area, TiO$_2$ compact layer might favor more interfacial contacts with the porous TiO$_2$/Nb$_2$O$_5$. These characteristics make TiO$_2$ compact layer deposited at substrate-nozzle distance of 150 mm with deposition duration of 60 seconds suitable for use as blocking layer. Longer deposition duration leads to more number of TiO$_2$ nanoparticles deposited on the substrate leading to increased film thickness, and as such, the optical transmittance decreases. The pores observed in films deposited with nozzle-substrate distance of 100 mm, figure (5.7) support optical and electrical behavior of these films. These
pores were responsible for the increased scattering in the thin films which is a factor responsible for the decrease in transmittance.

Figure 5.7: SEM micrograph of annealed TiO$_2$ compact layer of thickness 60 nm and 96 nm deposited by spray pyrolysis with nozzle-substrate distance of (a) 150 mm and (b) 100 mm deposited for 60 seconds respectively.

5.5 **SCOUT Modeling**

Using Drude and OJL models described in section 3.2.1 and 3.2.2 respectively of chapter 3 and considering the configuration of the semiconductor/substrate system, a best fit was obtained with ± 0.5 percent errors between the experimental point and the calculated transmittance. The successful fitting processes of the deposited films are in good agreement between the measured and calculated spectra as shown in figure 5.8.
Figure 5.8: Optical transmittance spectra for fitted and experimental data using SCOUT software based on Drude and OJL models

5.5.1 Effects of annealing on band gap energy of TiO₂ compact layer

The band gap energy \((E_g)\) was obtained by plotting \((\alpha hv)^2\) against \(hv\) based on Tauc equation, equation (3.3) in Chapter 3. Band gap energy was obtained by extrapolation of the target to the linear part of \((\alpha hv)^2\) vs \(hv\) curve where the intercept to \(hv\) gives the band gap energy. In principle, the band gap value strongly depends on crystal structure, morphology, and chemical composition of a given material (Rabeh et al., 2014).

Figure 5.9 shows the band gap energy for as-deposited and annealed TiO₂ compact layer. It is worth noticing that as-deposited films are characterized by high optical energy gap value of 3.7 eV. Annealing the thin films at 500 °C for one hour improves the crystallinity thereby decreasing the band gap energy to a value of 3.6 eV.
Annealing leads to improved crystallinity as supported by the XRD in figure 5.2. A change in optical band gap is given by the following equation (Agbo et al., 2012):

$$\Delta E_g = \frac{\hbar^2 \nu^2}{2r_\delta^2} \left( \frac{1}{M_e} + \frac{1}{M_h} \right) - \frac{(1.76e^2)}{\varepsilon_\infty r_\delta}$$

(5.4)

Where $M_e$, $M_h$ are the effective masses of electrons in the conduction band and holes in the valence band respectively and $\varepsilon_\infty$ is the static dielectric constant of the material. The first term represents the particle in a box quantum localization energy and has an inverse square relation $\frac{1}{r_\delta^2}$ dependence where $r_\delta$ is the grain size, while the second term represents the Coulomb
energy with $\frac{1}{r_\delta}$ dependence. Therefore as $r_\delta$ increases due to increase in grain growth due to annealing, the value of $\Delta E_s$ decrease (the crystallite size obtained was 18.59 nm and 19.76 nm for as-deposited and annealed thin films respectively). (Nandani et al., 2018) reported similar observation.

5.5.2 Effect of film thickness on band gap energy $E_g$ of TiO$_2$ compact layer

To understand the effect of film thickness of TiO$_2$ compact layer on the band gap energy, the deposition duration and nozzle-substrate distance were varied during the formation of compact layers. Figure 5.10 show the effect of film thickness on the band gap energy of annealed thin films. Decrease in the optical band gap with increase in film thickness is observed.

As the film thickness increases, the film begins to behave like a bulk material. In bulk materials, the crystallinity is enhanced, the defect states are decreased and the atoms become well packed as well as the crystallites get agglomerated. This indicates that the band gap value is influenced by the film thickness.

![Figure 5.10: Band gap energy for annealed TiO$_2$ thin films with varying thickness.](image-url)
These results suggest that the optical band gap of TiO$_2$ compact layer film could be controlled more precisely by controlling the thickness of the film. Thickness of the film causes a shift in the optical absorption edge. For bulk materials, the band gap energy ($E_g$) is constant. However, for thin crystalline films it varies with thickness due to the changes in barrier height at grain boundaries with increasing film thickness. This is due to increase in localized density of states near the edges and in turn decreases the value of $E_g$ with increase in film thickness (Alya and Akla, 2015). Equation (5.5) was used to explain and verify the band gap reduction with increase in film thickness (Goh et al., 2010).

$$\Delta E_g = \frac{\hbar^2}{2md^2}$$

where $d$ is the thickness of the film and $m$ is the effective carrier mass

### 5.5.3 Effects of annealing on Refractive index of TiO$_2$ compact layer

In the O’Leary-Johnson-Lim (OJL) model, refractive index $n_f$, as a function of energy is determined mainly by the parameter ‘mass’ which determines the shape of the conduction band (Solieman and Abu-Sehly, 2010). Figure 5.11 shows the variation of the refractive index with wavelength for as-deposited and annealed TiO$_2$ thin films. It is observed that the refractive index ($n_f$) is high for the annealed samples. This is because annealing causes decrease in porosity and structural transformation to crystalline anatase, which leads to increase in the refractive index of the film (Aksay and Altnokka, 2007).
Figure 5.11: Refractive index $n_f$ of as-deposited and annealed TiO$_2$ films of thickness 67 nm and 60 nm respectively.

5.6 Refractive Index $n_f$ and Porosity $P$

The refractive index of a thin film often differs from that of bulk material where thin films show lower values whereas the refractive index of thicker films approaches the bulk value. Within the film, it is convenient to use the concept of the porosity ($P$) which is defined to be the ratio of the average film density ($p_f$) and the bulk density ($p_m$)

$$p = \frac{p_f}{p_m}$$  \hspace{1cm} (5.6)

The dependence of refractive index on the film porosity could be easily explained by well-known Lorentz-Lorenz relation (Pulker, 1979)
Where \( n_m \) is the refractive index of pore-free anatase TiO\(_2\) and \( n_f \) is the refractive index of TiO\(_2\) compact layer film deposited by spray pyrolysis. The refractive index of dense anatase TiO\(_2\) is 2.46 (Asahi et al., 2000). Using equation (5.7) and the value of refractive index obtained for the films, the porosity of 60 nm thick layer was found to be 18.26 \( \% \) while that of 96 nm thick TiO\(_2\) layer was 12.89 \( \% \) respectively.

5.6.1 Effects of annealing on extinction coefficient \((k_{\lambda})\) of TiO\(_2\) compact layer

Figure 5.12 illustrates the extinction coefficient \( k_{\lambda} \) as a function of wavelength for as-deposited and annealed TiO\(_2\) blocking layers. It is observed that the extinction coefficient \( k_{\lambda} \) was generally higher for the annealed samples. This increase in extinction coefficient is attributed to decrease in the band gap energy when the film is annealed (Eiamchai et al., 2009).

![Extinction Coefficient vs Wavelength](image)

**Figure 5.12:** Extinction coefficient \( k_{\lambda} \) for as-deposited and annealed TiO\(_2\) films of thickness 67 nm and 60 nm respectively.
5.6.2 Effects of film thickness on extinction coefficient \( k_\lambda \) of TiO\(_2\) compact layer

Figure 5.13 shows extinction coefficient \( k_\lambda \) against wavelength curves for TiO\(_2\) compact layer with varying thickness. A decrease in extinction coefficient with increase in film thickness is observed. This can be explained using the relationship shown in equation (5.8) (Ilican et al., 2007)

\[
k_\lambda = \frac{\alpha \lambda}{4\pi d}
\]

(5.8)

Where \( d \) is the film thickness

![Graph showing extinction coefficient for TiO\(_2\) films of thickness 60 nm and 78 nm.](image)

**Figure 5.13**: Extinction coefficient \( k_\lambda \), for annealed TiO\(_2\) films of thickness 60 nm and 78 nm.

5.7 Electrical Characterization of TiO\(_2\) Compact Layer

5.7.1 Influence of annealing on electrical properties of TiO\(_2\) compact layer

Table 5.3 shows the values for the obtained sheet resistance of the films, charge carrier concentration \( n_a \), for different samples. The results indicate that the sheet resistance of the
samples decreases on annealing. Since TiO\textsubscript{2} is an n-type semiconductor, the concentration of Ti\textsuperscript{4+} in the TiO\textsubscript{2} films form a donor level between the band gap of TiO\textsubscript{2} which results in the reduction of recombination of photogenerated electron and holes (Zhao \textit{et al.}, 2008). Presence of O\textsuperscript{2-} ions results in an increase in the free electron concentration leading to decrease in film sheet resistance (Malati and Wong, 1984).

<table>
<thead>
<tr>
<th>TiO\textsubscript{2} compact Layer</th>
<th>Sheet resistance (×10\textsuperscript{2} Ωcm) (Experimental)</th>
<th>Sheet resistance (×10\textsuperscript{2} Ωcm) (Simulated)</th>
<th>Carrier concentration (×10\textsuperscript{22} cm\textsuperscript{-3})</th>
</tr>
</thead>
<tbody>
<tr>
<td>As-deposited</td>
<td>6.86</td>
<td>6.44</td>
<td>3.74</td>
</tr>
<tr>
<td>Annealed</td>
<td>4.86</td>
<td>4.55</td>
<td>3.5</td>
</tr>
</tbody>
</table>

Increase in conductivity upon annealing can as well be explained as follows; annealing results into reduction of surface energy which is a driving force for grain boundary enlargement facilitating electron mobility in the films and hence decrease in sheet resistivity (Biju and Jain, 2008). The carrier concentration is also seen to decrease on annealing of the thin films. Electrical carrier concentration \( n_a \) in the TiO\textsubscript{2} compact layers is seen to be very high and keeps within the order of magnitude of \( 10^{22}/\text{cm}^{3} \).

5.7.2 \textbf{Effect of film thickness on electrical properties of TiO\textsubscript{2} compact layer}

Table 5.4 shows the dependence of sheet resistivity and carrier concentration on the thickness of TiO\textsubscript{2} compact layer. It is observed that films with thickness 60 nm exhibited the lowest sheet resistivity of \( 1.33\times10^{2} \) Ωcm. However, as the thickness increased, the sheet resistivity of the films increased since it is inversely proportional to carrier concentration (Myoung \textit{et al.}, 2002).
The resistivity ($\rho$) of the thin films is proportional to the reciprocal of the product of free carrier concentration $n$ and the mobility ($\mu$) as shown in the following relation;

$$\rho = \frac{1}{en\mu}$$  \hspace{1cm} (5.9)

### Table 5.4: Influence of film thickness on electrical properties of TiO$_2$ compact layer

<table>
<thead>
<tr>
<th>TiO$_2$ compact layer thickness</th>
<th>Sheet resistance ($\times 10^2 \Omega \text{cm}$) (Experimental)</th>
<th>Sheet resistance ($\times 10^2 \Omega \text{cm}$) (Simulated)</th>
<th>Carrier concentration ($\times 10^{22} \text{ cm}^{-3}$)</th>
</tr>
</thead>
<tbody>
<tr>
<td>60 nm</td>
<td>1.23</td>
<td>1.33</td>
<td>5.58</td>
</tr>
<tr>
<td>78 nm</td>
<td>3.14</td>
<td>3.83</td>
<td>4.15</td>
</tr>
<tr>
<td>96 nm</td>
<td>4.86</td>
<td>4.55</td>
<td>3.50</td>
</tr>
<tr>
<td>120 nm</td>
<td>5.41</td>
<td>5.00</td>
<td>2.63</td>
</tr>
</tbody>
</table>

### 5.8 Optical Characterization of TiO$_2$/Nb$_2$O$_5$ Composite Thin Films

Variation of peak transmittance with concentration of Nb$_2$O$_5$ nanoparticles is shown in figure 5.14. A uniform thickness of 127 nm was maintained for all the composite thin film layers. It was noted that for higher concentrations of Nb$_2$O$_5$ absorption of light was enhanced thereby lowering the transmittance of the film. This behavior is an indication of increased charge carrier concentration in the composite as explained by the Drude’s theory (Pal et al., 2017).
Figure 5.14: Optical transmittance spectra for different composition of \( \text{Nb}_2\text{O}_5 \) in the \( \text{TiO}_2/\text{Nb}_2\text{O}_5 \) composite.

The SEM image figure 5.15(a) shows a network of interconnected \( \text{TiO}_2 \) and \( \text{Nb}_2\text{O}_5 \) nanoparticles formed from the mixture of the powders for \( \text{TiO}_2/\text{Nb}_2\text{O}_5 \) composite layer while figure 5.15 (b) shows the SEM micrograph for \( \text{TiO}_2 \) thin film. From the SEM images, the composite film is porous having a morphology that is favorable for light scattering effect and increases the light optical path, thus enhancing light absorption which makes the film appropriate for solar cells application, thus decrease in transmittance could be due to increased absorption of light as it travelled through the thicker films.
Figure 5.15: SEM micrograph of (a) TiO$_2$/Nb$_2$O$_5$ composite and (b) TiO$_2$ porous layer deposited by screen printing technique.

Figure 5.16 shows a plot of $(\alpha h\nu)^2$ versus $(h\nu)$ for determining the band gap energy. Direct band gap energies for pure TiO$_2$, Pure Nb$_2$O$_5$ and TiO$_2$/Nb$_2$O$_5$ composite were estimated by dropping a tangent to the linear part of the curves and extrapolating it to the intercept the energy $(h\nu)$-axis. The linear variation of $(\alpha h\nu)^2$ versus $(h\nu)$ at the absorption edge indicates direct transition took place across the band gap of the materials.

The obtained optical band gap energy for pure TiO$_2$ was found to be 3.90 eV, pure niobium was 3.95 eV and for TiO$_2$/Nb$_2$O$_5$ composite was 3.81 eV. These findings are in agreement with the findings of Nguu et al. (2014). It follows that the band gap energy obtained experimentally for the composite films was lower than those obtained for pure TiO$_2$ and pure Nb$_2$O$_5$ respectively. This observation could be as a result of development of sub-band states in the composite films (Nguu et al., 2014).
Figure 5.16: Variation of $(\alpha h\nu)^2$ versus photon energy $(h\nu)$ for direct band gap transitions in pure TiO$_2$, Pure Nb$_2$O$_5$ and TiO$_2$/Nb$_2$O$_5$ composite composite

5.9 Current-voltage (I-V) Characteristics

Figure 5.17 shows photocurrent against potential characteristics at 1 sun illumination for TiO$_2$/Nb$_2$O$_5$ dye sensitized solar cells with and without TiO$_2$ compact layer of varying thickness. Introduction of compact layer had an effect on $J_{sc}$ and $V_{oc}$ hence the conversion efficiency $\eta$ of the cells. Thin compact layer resulted in higher values of $J_{sc}$ and $V_{oc}$ with the highest value of $J_{sc}$ of 8.16 mA/cm$^2$ and efficiency of 3.39 % obtained for compact layer of 60 nm. Thick compact layer of 96 nm reported a reduction of $J_{sc}$ to 4.87 mA/cm$^2$ and 1.29 % efficiency. Comparatively, cells without compact layer had lower $J_{sc}$ of 3.68 mA/cm$^2$ and efficiency 1.90 %.
The improved $J_{sc}$ and efficiency can be explained to be as a result of improved adherence and increased electron pathways and therefore less resistance to electron transfer to the FTO interface (Ito et al., 2008). The compact layer favors the accumulation of electrons at the interface of FTO resulting in an upward shift of electron Fermi level by increasing the electron-carrier concentration (O’Regan et al., 2005). As a result, higher $V_{oc}$ is obtained compared to the bare cell, and the short-circuit current density $J_{sc}$ is also increased. The experimental results we obtained for TiO$_2$/Nb$_2$O$_5$ composite layer without a compact layer are similar those obtained by Jose et al. (2009) and Nguu et al. (2014). Introduction of compact layer enhanced the photoconversion efficiency of the cells.

Decrease in conversion efficiency was observed for thicker compact layer (96 nm). One possible reason is that more trap states exist in the thicker TiO$_2$ compact layer which tend to block the pathway of photo excited electrons from the nanoporous TiO$_2$/Nb$_2$O$_5$ layer to the FTO electrode.
(Zhang et al., 2005). Furthermore, the thicker TiO₂ compact layer lowers optical transmittance, thereby reducing both $J_{SC}$ and $V_{OC}$.

The series resistance $R_s$ and shunt resistance $R_{sh}$ values of the device are presented in Table 5.5. As is well-known from the equivalent circuit model, $R_{sh}$ relates to the interface recombination in the cells. Thus a higher $R_{sh}$ corresponds to the suppression of charge recombination inside the cells, which in turn results in a higher $V_{oc}$. Series resistance in the cells is associated with charge transfer at Pt-counter electrode, FTO substrate resistance and the Nernst diffusion in the electrolyte (Yang et al., 2012). With introduction of compact layer, decrease in series resistance was observed which to increase in fill factor. This was as a result of electron permeating into the compact layer which then blocks its recombination. However, for very thick compact layers, an increase in series resistance of the cells was noticed. This could be as a result of existence of more trap states in the thick layers hindering the electron transfer at the Pt counter electrode. Compact layers of thickness less than 50 nm could not be achieved experimentally due to the employed deposition technique and instruments limitations. It is important to note the conversion efficiency of the solar cells having 60 nm thick TiO₂ blocking layer displays a decent photovoltaic performance comparable to those reported in literature (Supasai et al., 2016; Concina and Vomiero, 2015). It is worth noticing that there is deterioration in photovoltaic parameters with increase in compact layer thickness.
The photovoltaic parameters, open circuit voltage $V_{OC}$, short circuit current density $J_{sc}$, fill factor ($FF$) and the conversion efficiency ($\eta$) were obtained from the $J$-$V$ characteristic curves together with the following equations.

\[
FF = \frac{P_{max}}{P_{in}} = \frac{J_{max} V_{max}}{J_{sc} V_{OC}}
\]

\[
\eta = \frac{J_{sc} V_{OC} FF}{P_{in}}
\]

Where $V_{max}$ is the maximum voltage, $J_{max}$ is the maximum current density (mA/cm$^2$) and $P_{in}$ incident light intensity (mW/cm$^2$).

From figure 5.18 gives a summary of various cells parameter with varying thickness. It was observed that for DSSCs with thicker compact layers, the photovoltaic parameters deteriorate.
Figure 5.18: Variation of photovoltaic parameters of dye sensitized solar cells with varying TiO$_2$ compact layer thickness (a) current density $J_{sc}$ (mA/cm$^2$), (b) Fill factor FF, (c) Efficiency $\eta$ and (d) Open circuit voltage $V_{OC}$.

5.10 Electrochemical impedance spectroscopy

To gain further insight into the interfacial charge transport in the fabricated DSSCs, electrochemical impedance spectroscopy was performed. Figure 5.19 shows the Nyquist plots of solar cells based on different TiO$_2$ compact layer thickness and zoom of Nyquist plots at high frequency region. The spectra obtained are characterized by major RC arc and some additional minor features in the high frequency region. The semicircles are almost perfect but at high frequency there is a small additional arc which is due to the internal resistance of the solar cells. The high frequency arc (Zoomed) is attributed to the redox reaction at the platinum counter
electrode while the larger arc is as a result of reactions at the metal oxide semiconductor/electrolyte interface (Basu et al., 2016).

The high frequency part contain information of transport and series resistance element as well as the dielectric contributions while the arc at low frequencies is attributed to recombination resistance ($R_{\text{rec}}$) and chemical capacitance ($C_\mu$) of the device (Garcia-Belmonte et al., 2008).

The arc observed at mid-frequency accounts for electron diffusion in the TiO$_2$ layer, and a RC element (R-resistor C-capacitor) where recombination resistance and chemical capacitance are expressed as

![Figure 5.19](image-url)
\[
R_{\text{rec}} = R_o \exp \left( \beta \frac{eV}{k_B T} \right) \\
C_\mu = C_o \exp \left( \alpha \frac{eV}{k_B T} \right)
\] (5.13)

Where \( C_o \) and \( R_o \) are constants, \( e \) is the elementary charge, \( k_B \) is Boltzmann’s constant, \( T \) is the absolute temperature, \( \beta \) and \( \alpha \) are dimensionless parameters and \( V \) is the voltage.

The recombination resistance \( R_{\text{rec}} \) produces a rather direct view of the recombination process in the cells. It is attributed to the processes in the TiO\(_2\)/electrolyte interface. The second arc is evidently large for the solar cells with TiO\(_2\) compact layer indicating that the compact layer increases \( R_{\text{rec}} \) thus lowering the recombination processes at the oxide/electrode interface leading to a larger \( V_{\text{oc}} \) (Gôes et al., 2012). Introduction of blocking layer of desired thickness increases the electron lifetime \( \tau \) by suppressing recombination at the FTO/electrolyte interface (Yoo et al., 2010). The longest lifetime is obtained from DSSC with 60 nm thick TiO\(_2\) compact layer. This is the optimum thickness at which the cells exhibit the highest conversion efficiency.

Chemical capacitance \( C_\mu \) accounts for accumulation of electrons in the localized states located in the TiO\(_2\) and Nb\(_2\)O\(_3\) band gaps (Todinova et al., 2015). It measures the capability of a system to accept or release additional electrons due to variation of its Fermi level.

Transport resistance \( R_\tau \) corresponds to electron diffusion through the TiO\(_2\)/Nb\(_2\)O\(_5\). For thicker compact layer, increase in \( R_\tau \) is observed. This is because of existence of more trap states which block the movement of photo-generated electrons. The trend in series resistance \( R_s \) for DSSC with TiO\(_2\) compact layer is smaller than that of bare DSSC which is consistent with the results
obtained from $J-V$ curves. In both cases DSSC fabricated using 60 nm thick compact layer showing the lowest series resistance while bare cells shows the highest series resistance. The measured values of recombination resistance $R_{\text{rec}}$, transport resistance $R_{\text{tr}}$, electron lifetime $\tau$, geometrical capacitance $C_g$, chemical capacitance $C_{\mu}$ and series resistance $R_s$ are shown in Table 5.7

<table>
<thead>
<tr>
<th>TiO$_2$ compact layer thickness with 127 nm thick TiO$_2$/Nb$_2$O$_5$ porous layer</th>
<th>$R_{\text{rec}}$ (Ohm.cm$^2$)</th>
<th>$C_{\mu}$ ($\times 10^{-6}$ F/cm$^2$)</th>
<th>$R_{\text{tr}}$ (Ohm.cm$^2$)</th>
<th>$C_g$ ($\times 10^6$ F/cm$^2$)</th>
<th>$R_s$ (Ohm.cm$^2$)</th>
<th>$\tau$ ($\times 10^{-8}$s)</th>
</tr>
</thead>
<tbody>
<tr>
<td>60 nm</td>
<td>899.36</td>
<td>43.00</td>
<td>453</td>
<td>8.82</td>
<td>10</td>
<td>386.90</td>
</tr>
<tr>
<td>78 nm</td>
<td>333.20</td>
<td>27.50</td>
<td>27</td>
<td>62.10</td>
<td>16</td>
<td>91.50</td>
</tr>
<tr>
<td>Bare</td>
<td>54.91</td>
<td>4.60</td>
<td>12</td>
<td>81.20</td>
<td>21</td>
<td>2.50</td>
</tr>
</tbody>
</table>

Nyquist plots at different bias voltages varied between 0.5 - 0.70V were also analyzed. Figure 5.20 shows the Nyquist plot at different bias voltages. It was noted that the diameter of the semicircles reduce with increase in bias voltage due to the sinking recombination resistance which is dependent on recombination current.
Increase in bias voltage leads to decrease in resistance. This led to arc at high frequencies to become more pronounced and can be assigned to a fast diffusion of electrons through the TiO$_2$ compact layers. Recombination resistance decreases from 401 Ωcm$^2$ at 0.5 V to 85 Ωcm$^2$ at 0.7 V. $R_{rec}$ is dependent on the voltage due to the increased charge carrier densities while the chemical capacitance rises exponentially with increase in bias voltage since it has a direct dependence on the charge carrier densities (Leever et al., 2012). Figure 5.21 shows a plot of parameters in equivalent circuit against bias voltage for the best performing solar cell.
Figure 5.21: Impedance spectroscopy measurements of the best performing DSSCs with TiO₂ compact layer of 60 nm thickness.
CHAPTER SIX
CONCLUSION AND RECOMMENDATIONS

6.1 Conclusion

This project was aimed at developing blocking layer based on titanium dioxide and studying its effect on the photovoltaic characteristics of TiO$_2$/Nb$_2$O$_5$ composite dye sensitized solar cell. In this study, investigation on the deposition of TiO$_2$ blocking layer by spray pyrolysis technique was successfully performed to determine the correlation between the deposition conditions and the electrical properties of the grown thin films. We demonstrated that the thickness of the films is determined by deposition time and varying the deposition distance between the substrate and the spray nozzle. It was noted that the electrical resistivity of the deposited TiO$_2$ compact layers can be manipulated by annealing the films to 500 °C.

Optical, morphological and structural properties of films were performed by UV-VIS spectrophotometer, scanning electron microscope, Raman spectroscopy and X-ray diffraction respectively. Characterization of the optical properties of the films revealed the dependence of transmittance of the films to thickness. XRD results obtained in this work indicated that changes in electrical resistivity of the films are associated to the structural changes where annealed films showed to be highly crystalline thereby lowering the resistivity of the films.

From current density- voltage (J-V) characteristics of the assembled cells, it can be concluded that current-voltage characteristics of the cell are affected by introduction of a blocking layer where a cell incorporating 60 nm thick compact layer exhibiting the highest efficiency of 3.39 % with current density $J_{sc} = 8.16 \ mA/cm^2$, open circuit voltage $V_{oc} = 0.719V$ and fill factor $FF = 0.578$. 

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In comparison, a cell without compact layer showed relatively low efficiency $\eta$ of 1.90, short circuit current $J_{sc}=4.84$ mA/cm$^2$, open circuit voltage $V_{oc}=0.676$ V and fill factor $FF$ equals to 0.578.

Electrochemical impedance spectroscopy analysis was performed to extract the parameters corresponding to fundamental electronic and ionic processes in the cells. Nyquist plots were obtained at bias voltage of 0.6 V and the spectra fitted to an appropriate equivalent circuit to extract key parameters; recombination resistance $R_{rec}$, series resistance $R_s$, Transport resistance $R_{tr}$, lifetime $\tau$ and chemical capacitance $C_\mu$. The study revealed that introduction of TiO$_2$ compact layer increased recombination resistance in the cells leading to improved $V_{oc}$. For the best performing cell, recombination resistance $R_{rec}$ was 899.36 Ohm.cm$^2$, chemical capacitance $C_\mu=4.3\times10^{-5}$ Fcm$^{-2}$, transport resistance $R_{tr}$ 4.53$\times$10$^{2}$ Ohm.cm$^2$, geometrical capacitance $C_g=8.82\times10^{-6}$ Fcm$^{-2}$ and recombination resistance $R_s=10$ ohm.cm$^2$. Charge carrier life time of the solar cells were also determined with the best performing solar cell having charge carrier lifetime of $3.86\times10^{-2}$ s while charge carrier lifetime for solar cell showing lowest efficiency to be $2.50\times10^{-4}$ s. From the study, was noted that TiO$_2$ compact layer improved the performance of dye sensitized solar cells due to improved open circuit voltage and fill factor while for very thick compact layer, the efficiency dropped.

6.2 Recommendations

The study of effects of TiO$_2$ compact layer on PV characteristics of Nb$_2$O$_5$ composite solar cells still remains at fundamental levels. For future research, there is need to study the effect of varying precursor concentration on the optical and electrical properties of TiO$_2$ compact layer. Further, it is recommended that effects of thickness of TiO$_2$/Nb$_2$O$_5$ composite layer on the conversion efficiency of solar cells be studied.
References


